X線ナノ集光技術の展望

大阪大学　山内和人

Collaborators

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SPring-8

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H. Mimura,

Acknowledgement

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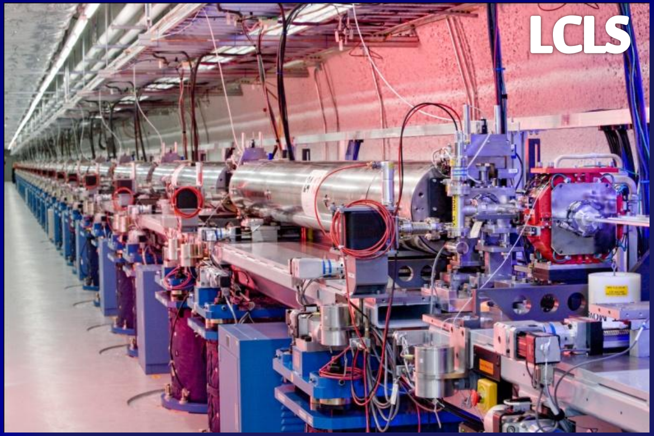
Background and today's contents

3rd generation SR facilities widely contribute to many S&T fields.
4th generation facility (XFEL) has already been here.



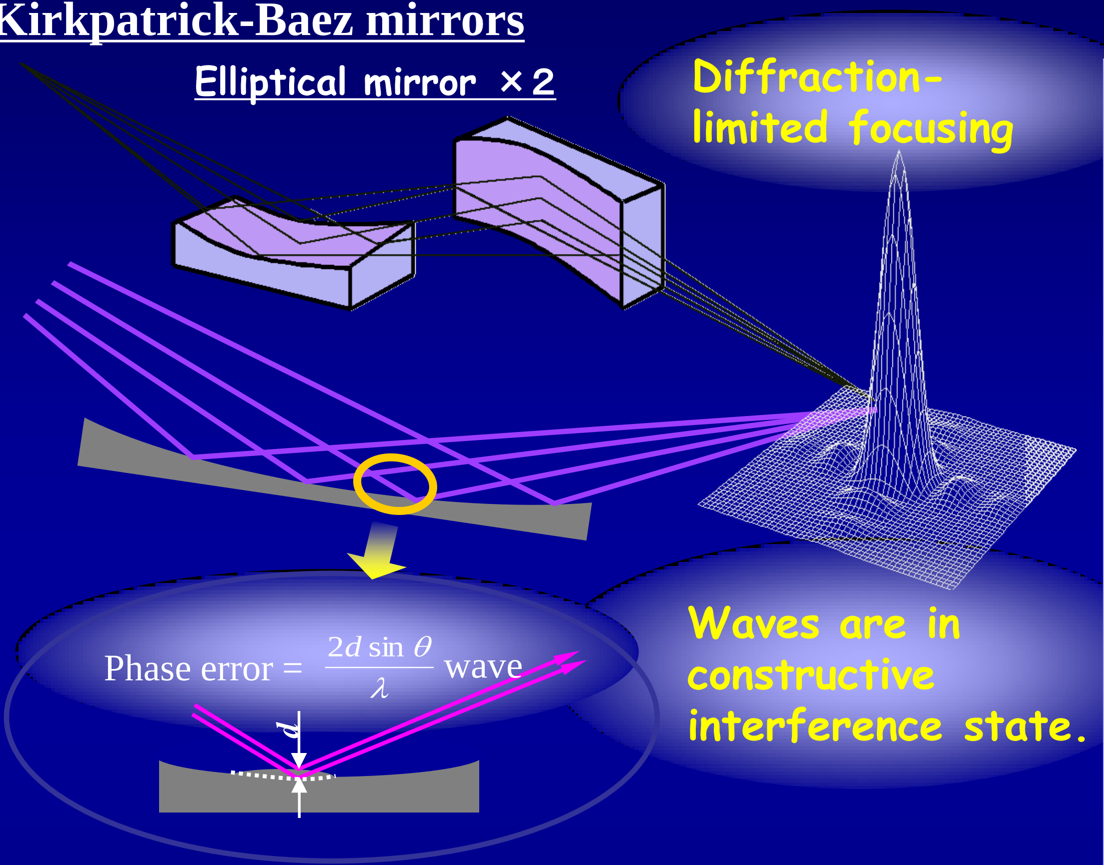
How should mirror optic contribute to advanced X-ray optical system?

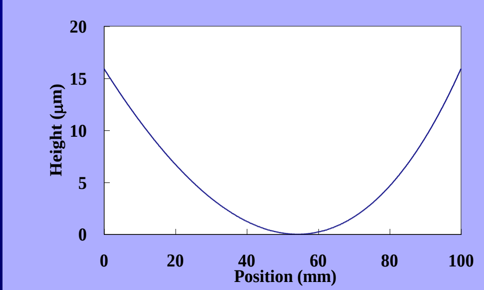
Current research targets

1. Focusing down to sub-10nm (including brief introduction of sub-50nm focusing)
2. Full-field, achromatic and high-resolution imaging of incoherent X-rays
3. XFEL focusing (400mm-long mirror development)
4. Focused beam diffraction microscopy

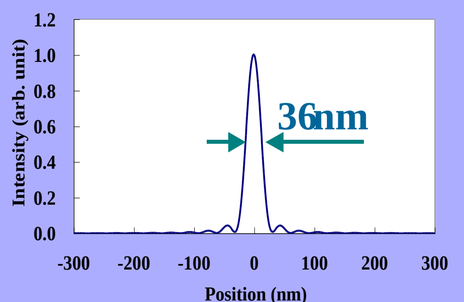
Required accuracy for nano-focusing under D-limited condition

Kirkpatrick-Baez mirrors

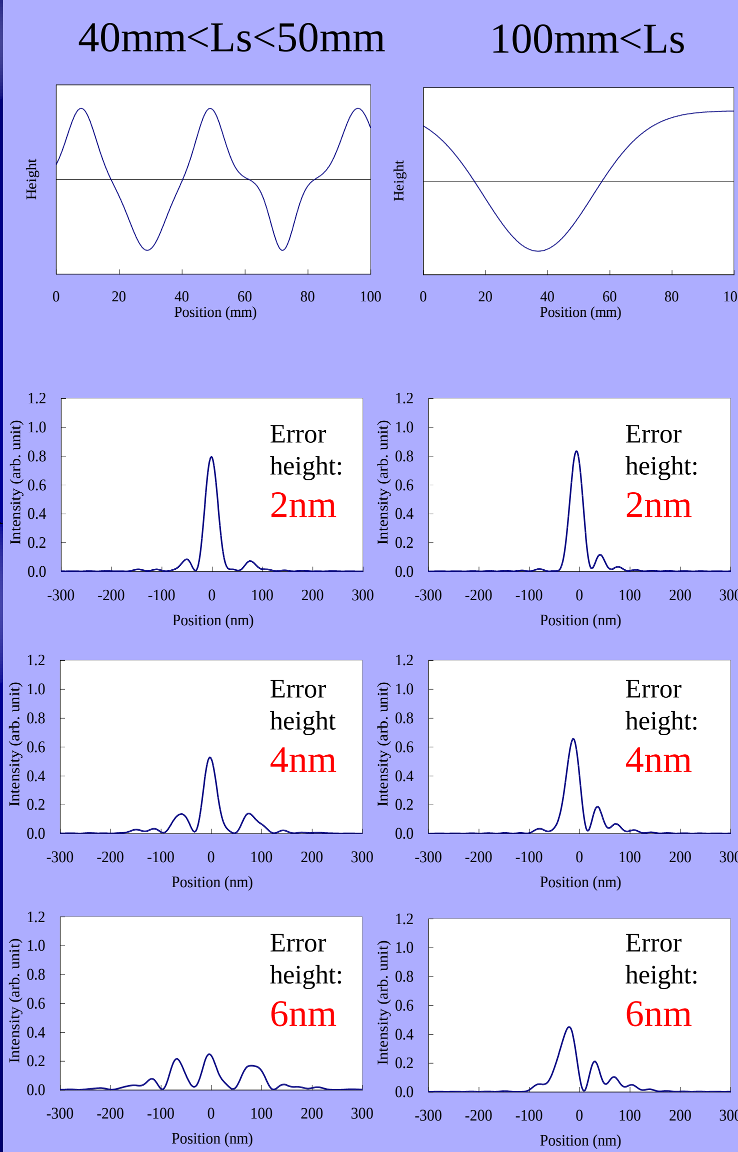




Designed profile (ellipse)



Beam profile



Fabrication and figure testing technologies of Osaka University

◎ Plasma CVM (chemical vaporization machining)

→ Rough figuring (Rapid figuring with 10nm (P-V) level accuracy)

K. Yamamura et al., Rev. Sci. Instrum. 71 (2000), 4627

◎ EEM (elastic emission machining)

→ Final figuring and smoothing (Fine figuring with atomically smoothing)

K. Yamauchi et al., Rev. Sci. Instrum. 73 (2002), 4028

◎ MSI (microstitching interferometry)

→ Figure tester with spatial resolution close to 0.01mm

K. Yamauchi et al., Rev. Sci. Instrum. 74 (2003), 2894

◎ RADSI (relative-angle determinable stitching interferometry)

→ Figure tester for steeply curved ellipse of large NA mirror

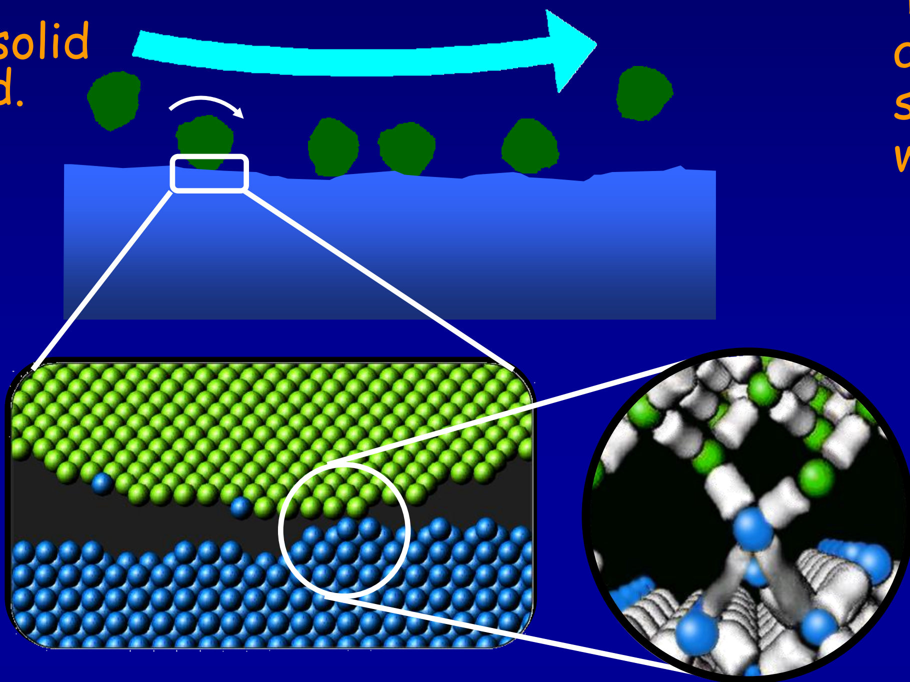
H. Mimura et al., Rev. Sci. Instrum. 76 (2005), 045102

JTEC URL http://www.j-tec.co.jp

Removal mechanism of EEM (Elastic Emission Machining)

In EEM, chemical reaction between solid surfaces is utilized.

Ultrapure water flow

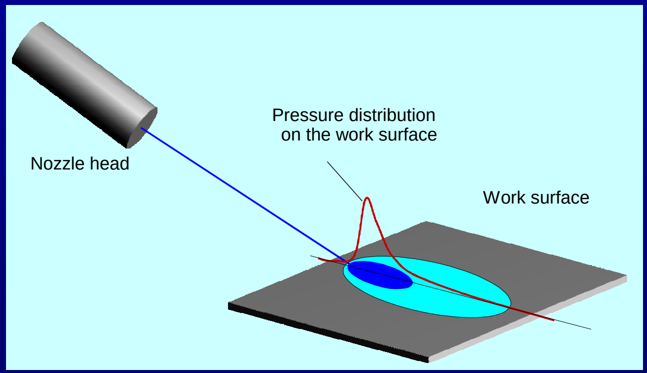


The ultra-fine particles are supplied to the work surface by ultrapure water flow

Atom-by-atom removal

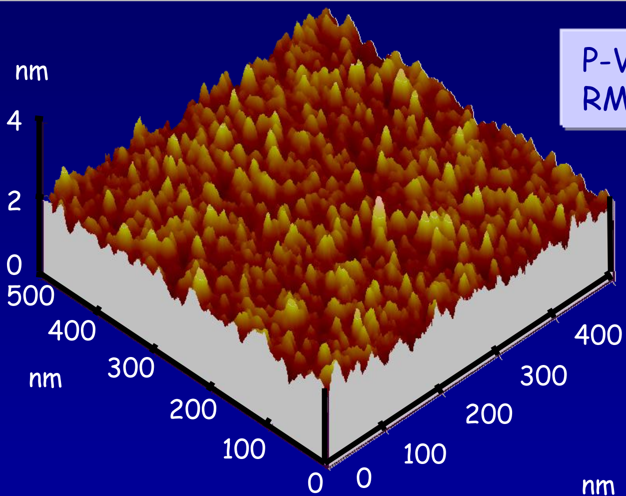
Bump site is preferentially removed

Atomically flat surface can be obtained



Deterministic figuring

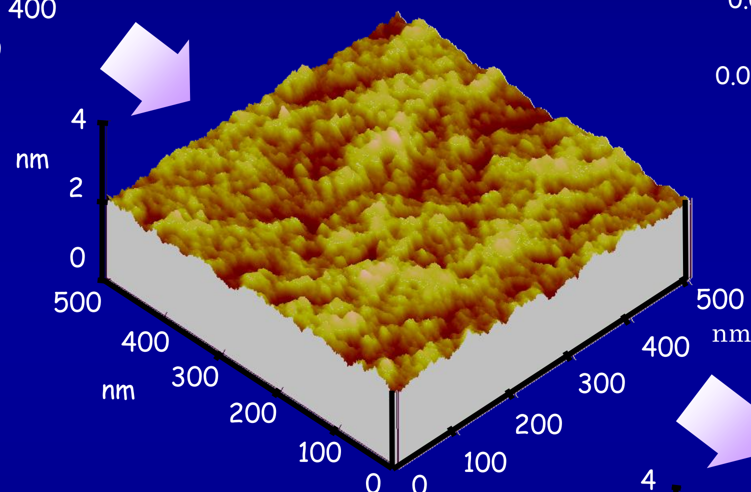
Surfaces smoothing properties in EEM



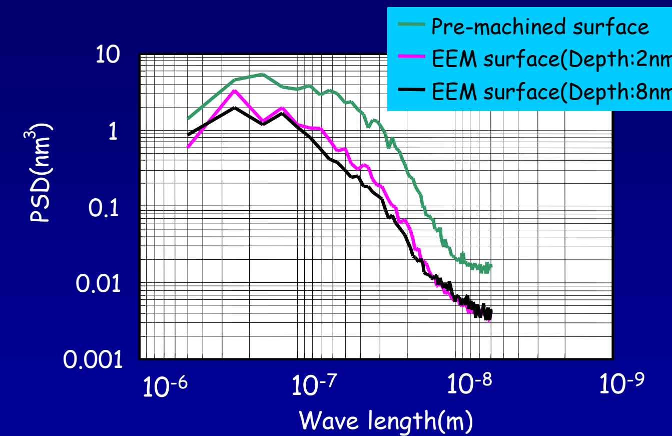
P-V 1.603 nm
RMS 0.183 nm

Pre-machined surface

P-V 0.910 nm
RMS 0.100 nm

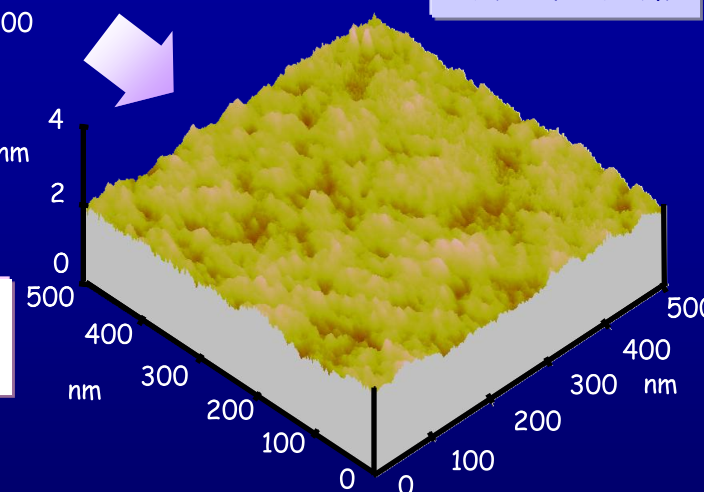


EEM surface (Removal depth:2nm)



PSD analysis

P-V 0.769 nm
RMS 0.087 nm

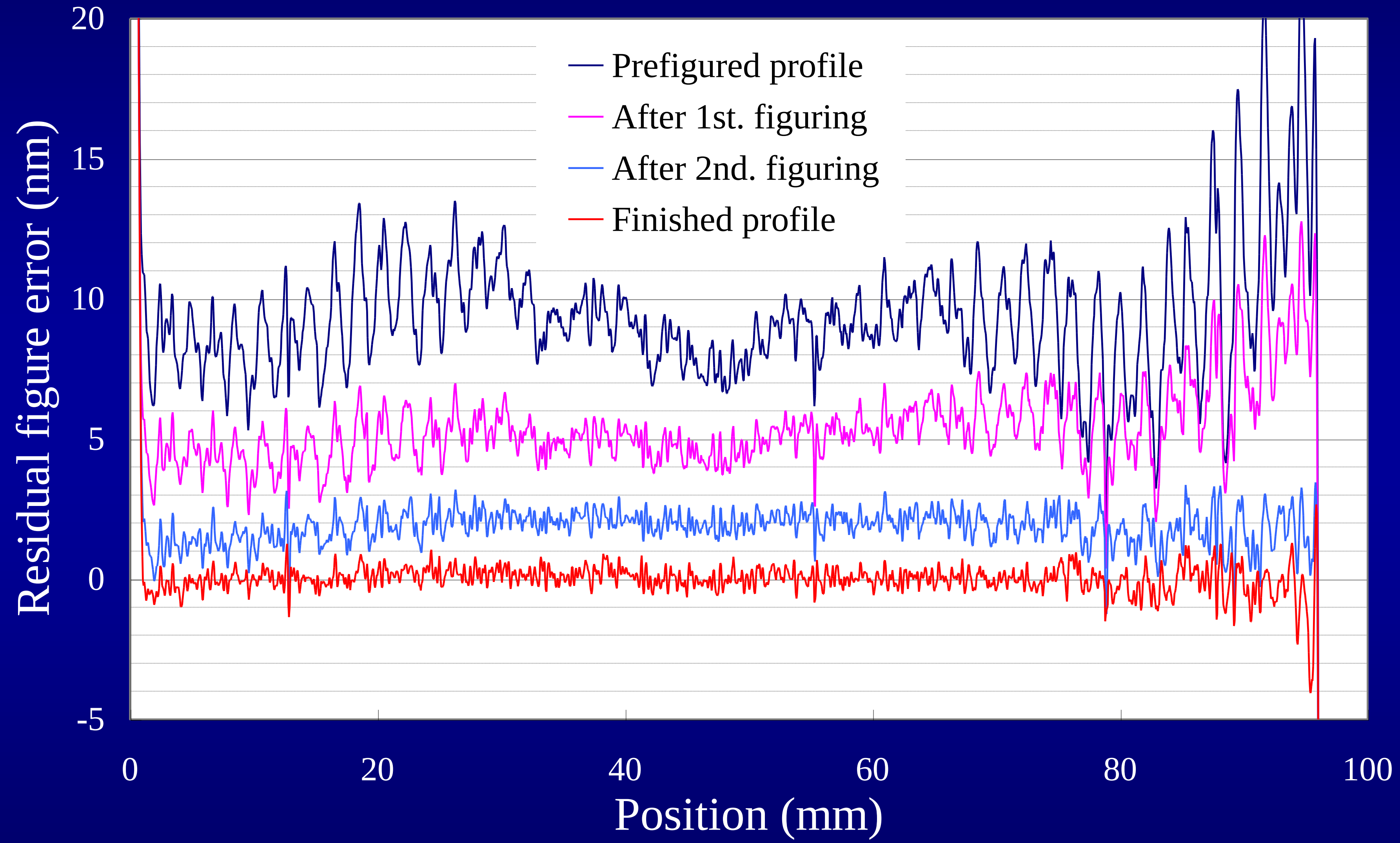


EEM surface (Removal depth:8nm)

Surface with the roughness of about 2nm (P-V) can be smoothened within the removal depth of 2nm.

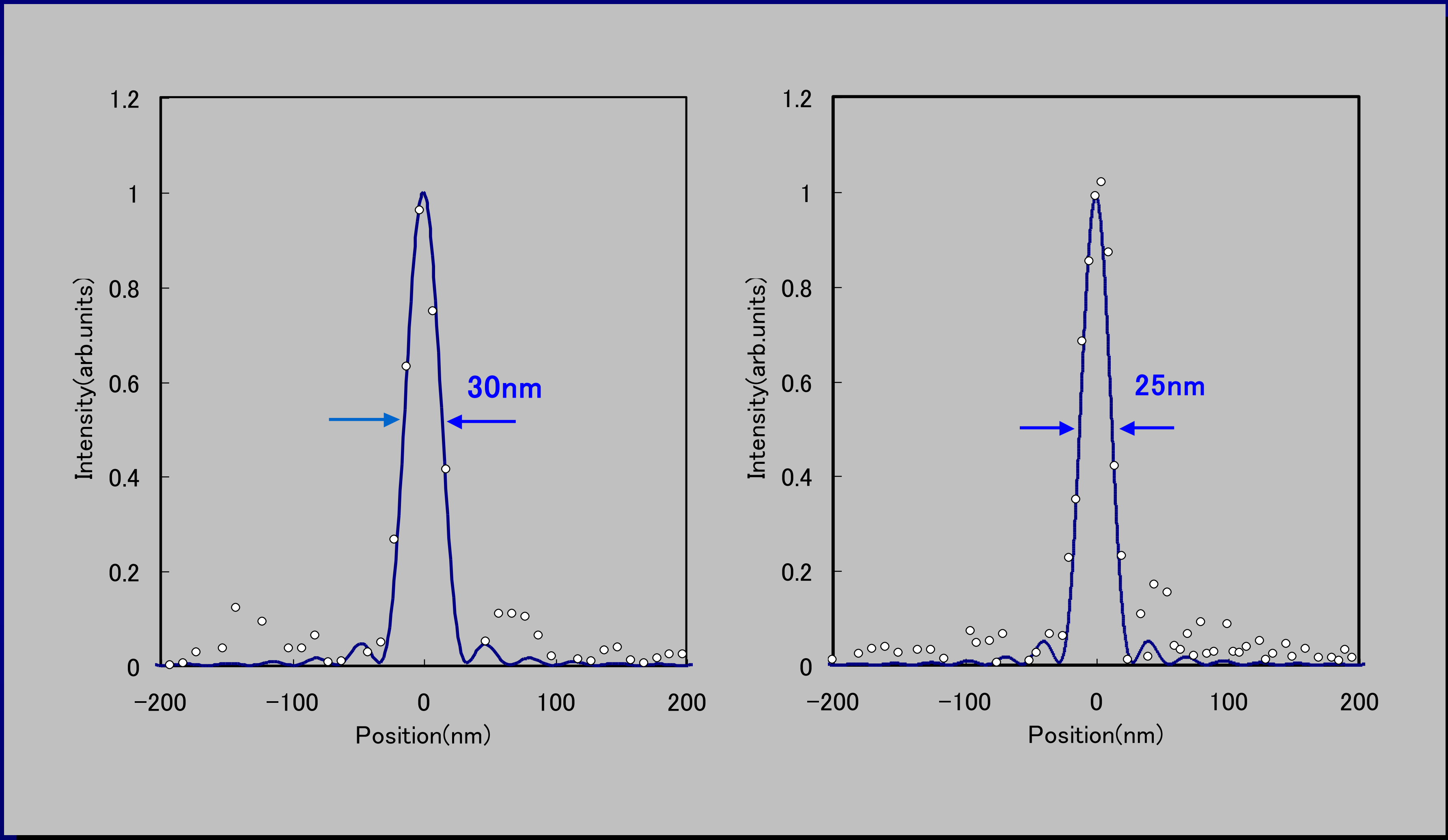
The bump site is selectively removed.

Typical deterministic figuring properties using EEM



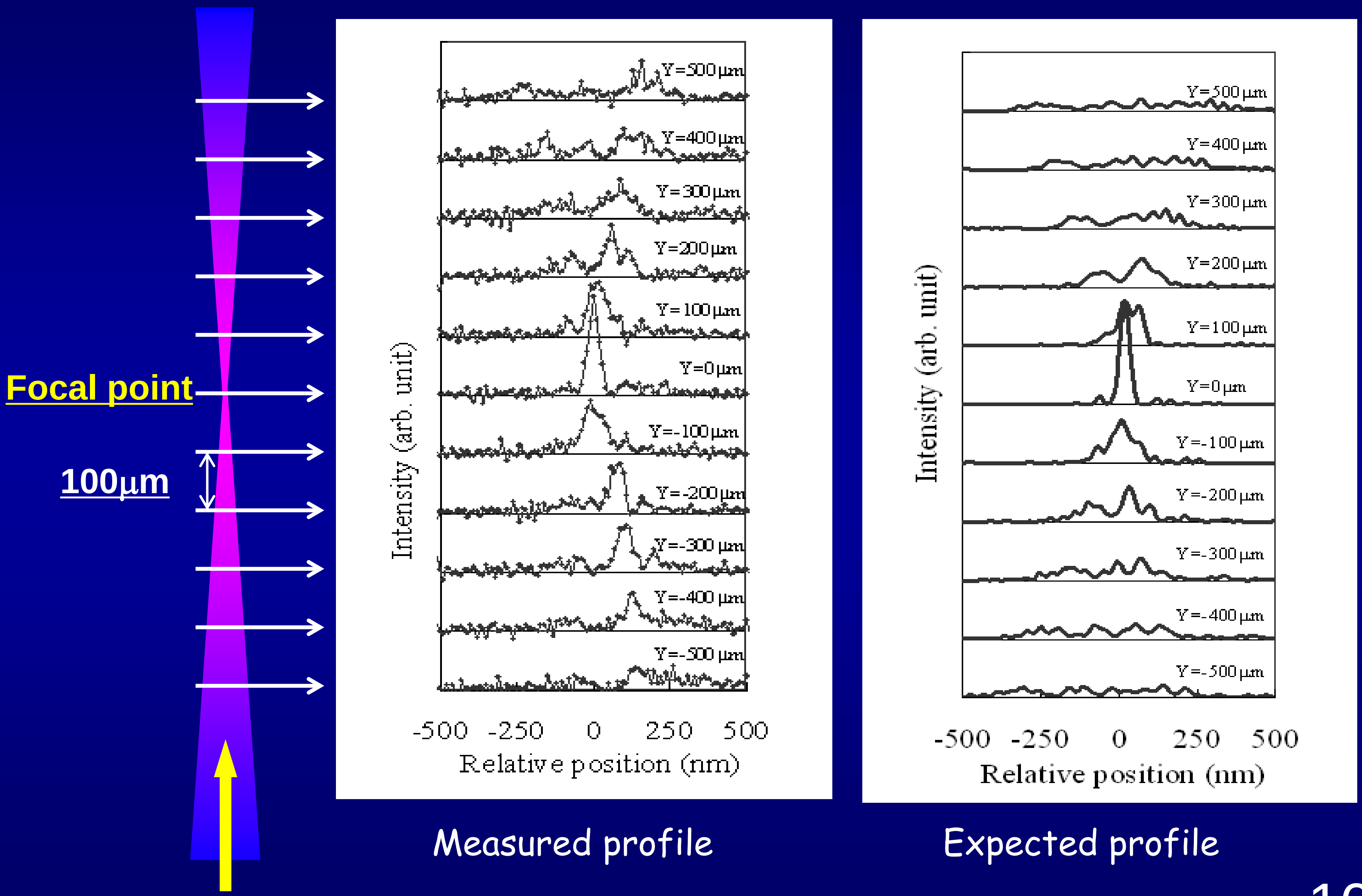
Sub-30nm focusing (2006)

Smallest size in hard-X-ray realized by total reflection achromatic mirror optics (focusing under diffraction limited condition)

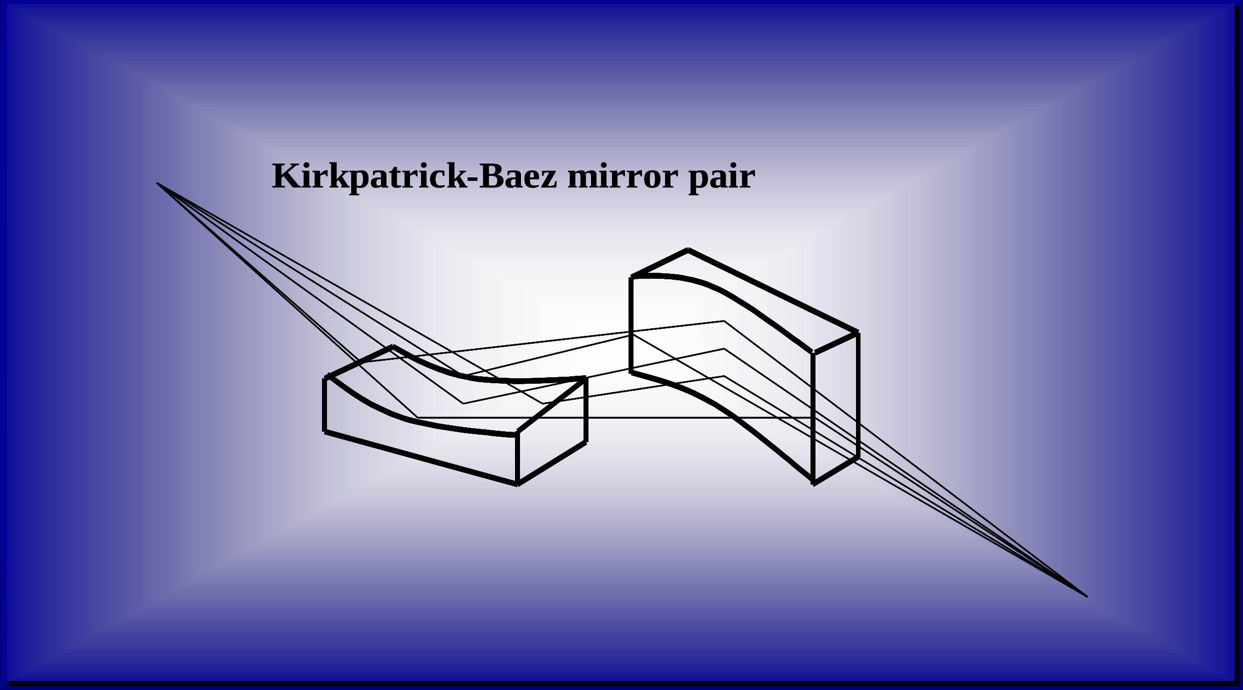


Mimura et al., APL (2007)

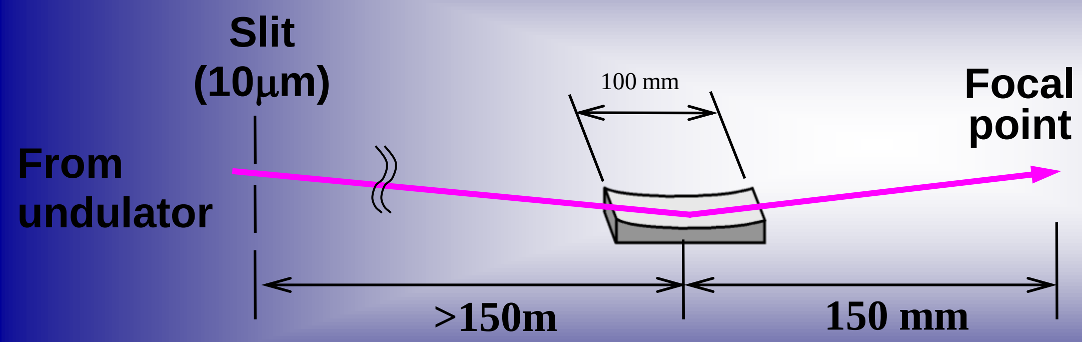
Beam waist structures



"Hard-X-ray sub-10nm focusing and realization of high-resolution X-ray microscopy"



To realize Sub-10nm focusing K-B mirrors

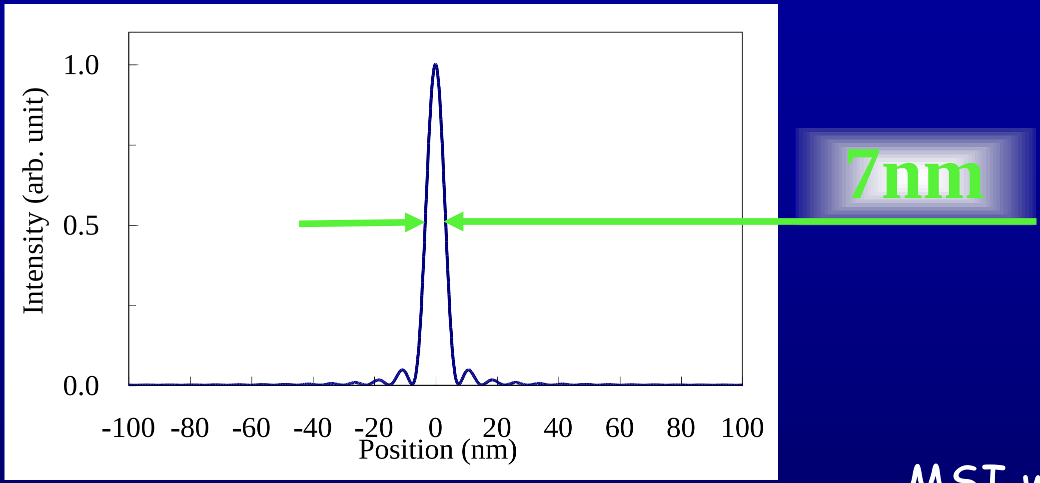


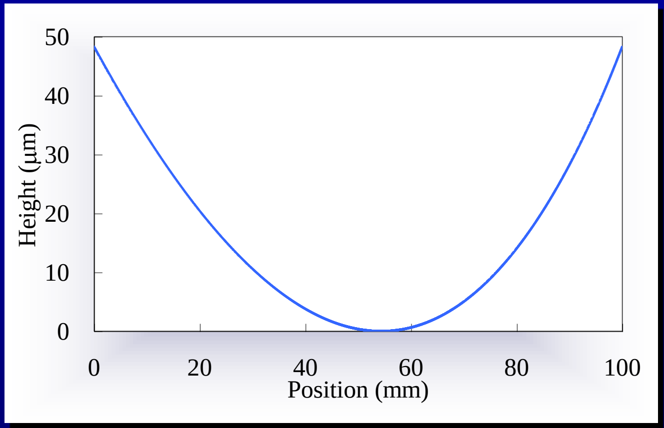
X-ray energy : 20keV

Focal length : 150mm

Acceptance width : 1.1mm

Incidence angle : 11.1mrad





MSI with RADSI and EEM can prepare the surface figure with 1nm (P-V) accuracy.

Estimation of required accuracy

@20keV Mirror length: 100mm, Focal length: 150mm

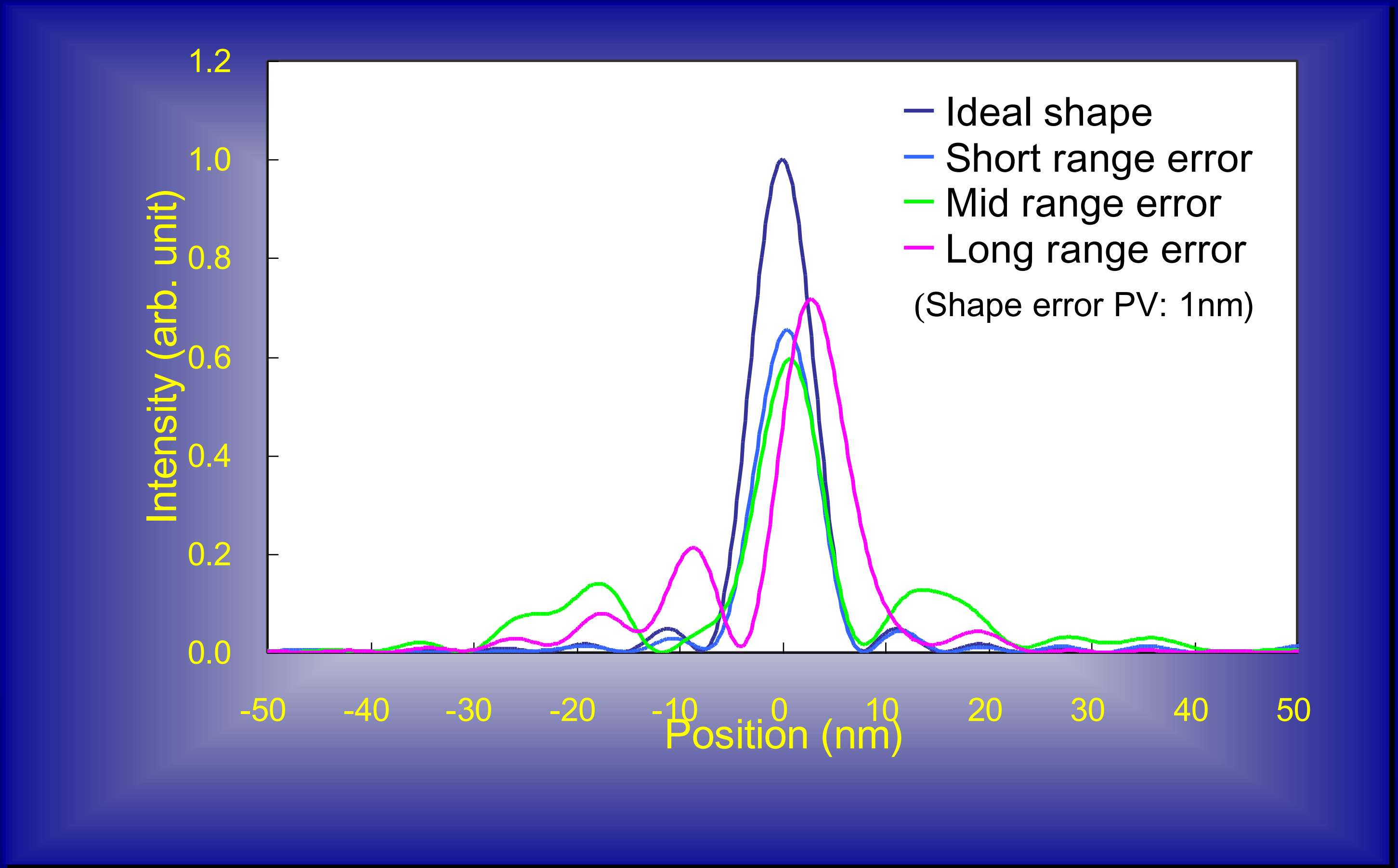
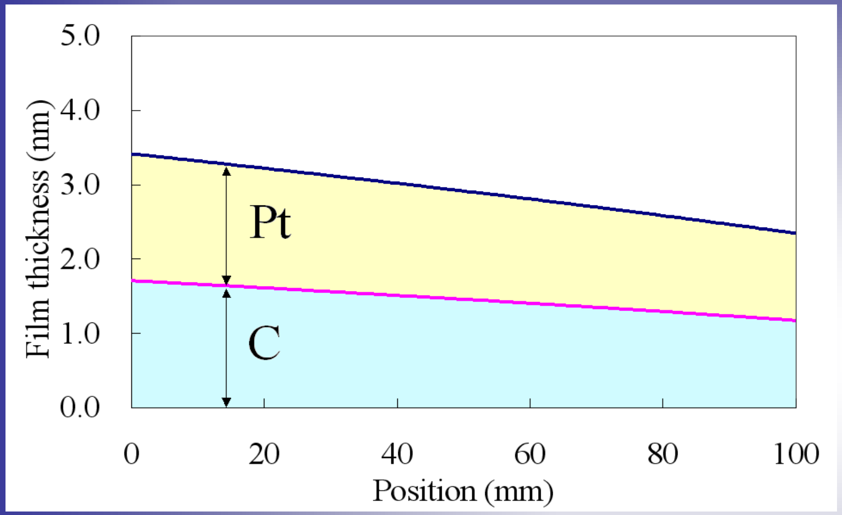
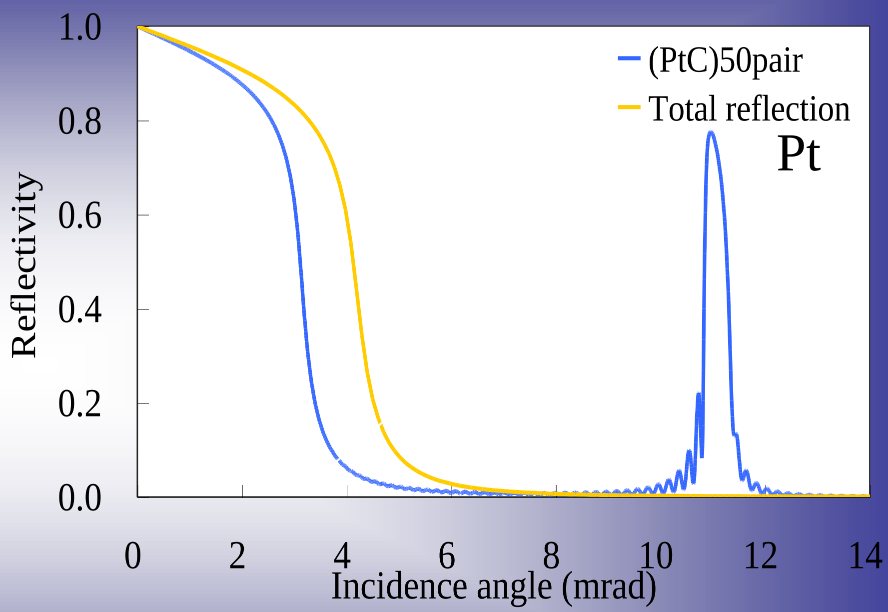


Figure error of 1nm is not allowable

Multi-layer technology is needed to realize large NA



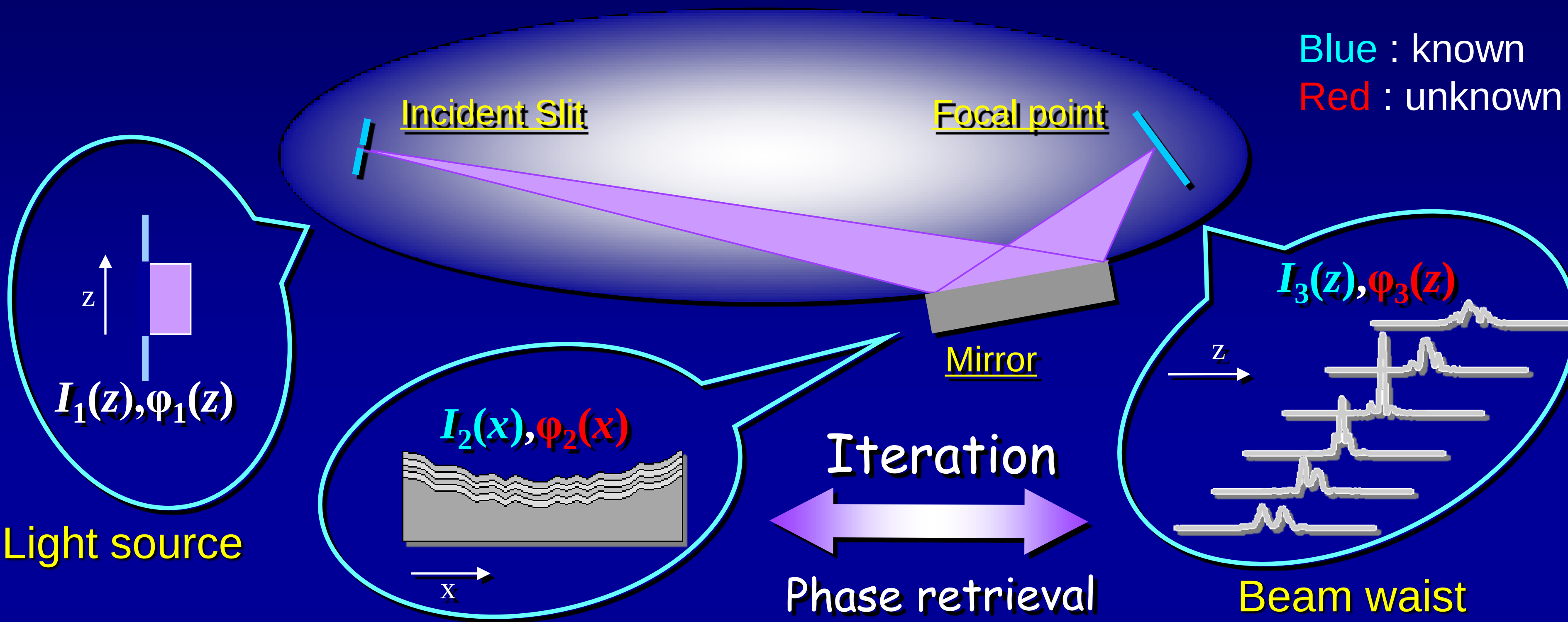
Graded multi-layer



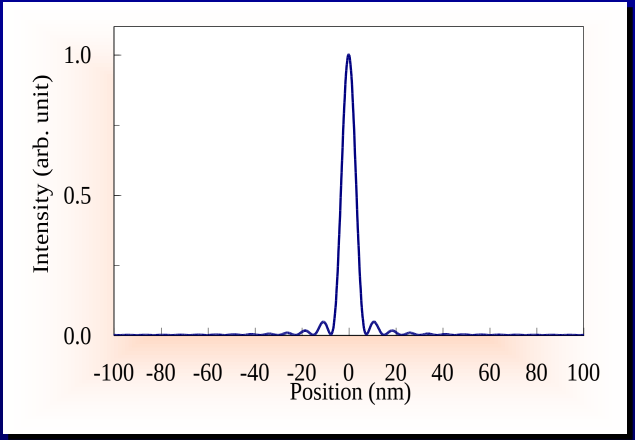
Reflectivity

Not only figure error but also thickness deviation of the multilayer induce wavefront phase error.

At-wavelength phase-retrieval interferometry



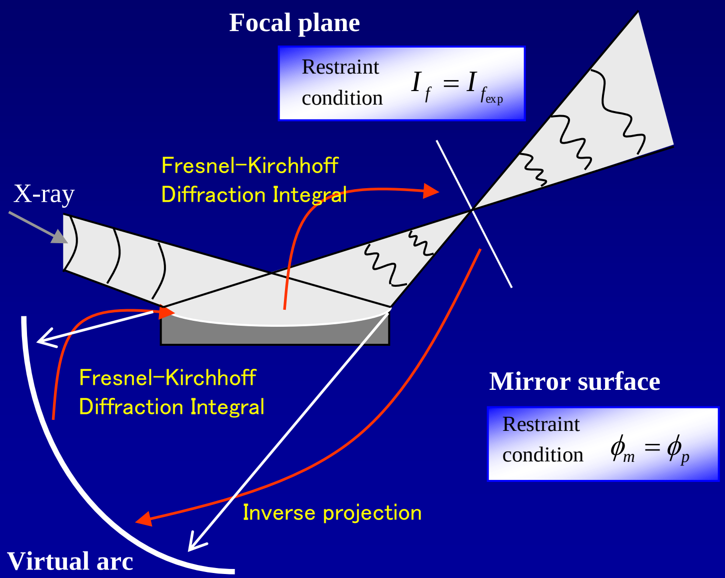
Mirror surface
(Phase error includes surface figure and ML thickness errors)

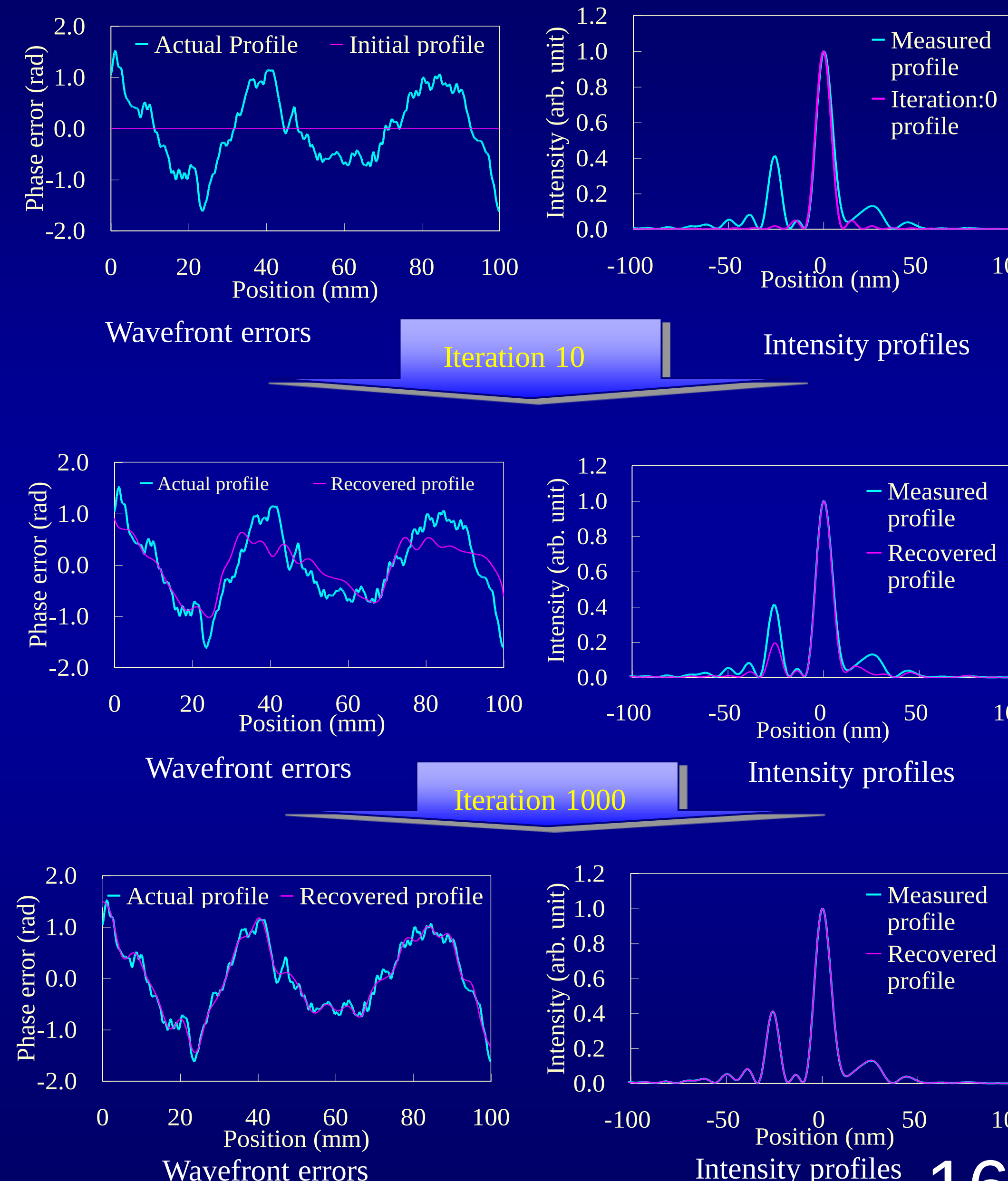


Phase error compensation

K. Yamauchi,
SPIE's Optics and Photonics 2005

Phase retrieval properties





On focal plane

Intensity is changed to experimental value.

Phase is kept to be recovered value.

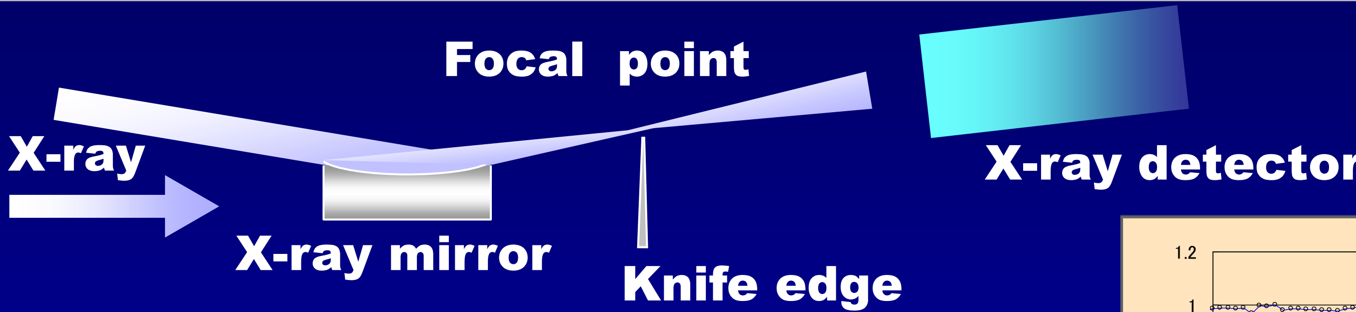
On mirror surface

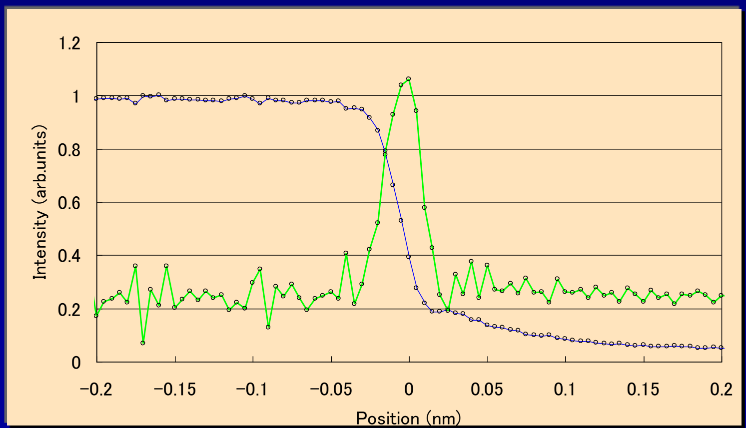
Intensity is changed to theoretical value.

Phase is kept to be recovered value.

Yumoto et al.,
Rev. Sci. Instrum. (2006)

New knife-edge method

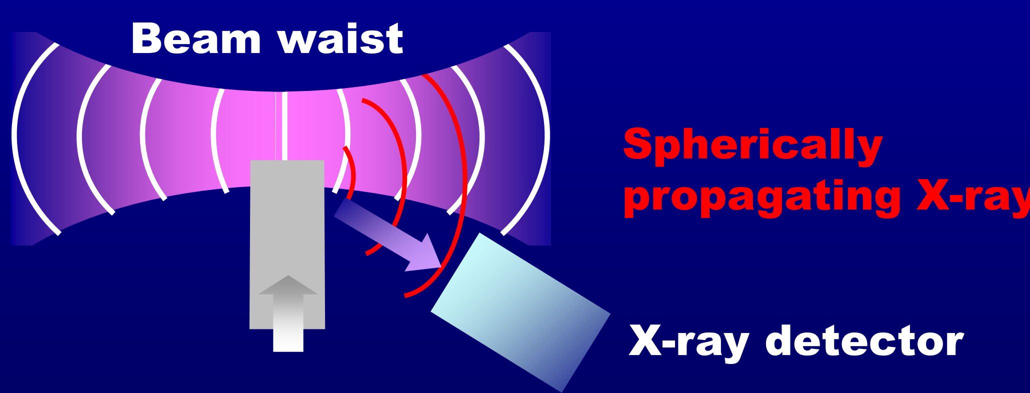




Conventional knife-edge method

↓

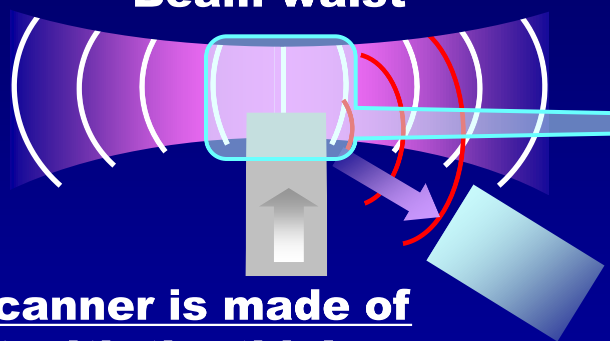
New method



Mimura et al.
Phys. Rev. A (2008)

Details of the new knife-edge method

Beam waist

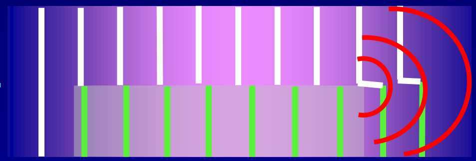


Scanner is made of Pt with the thickness of 2.5μm.

Spherically propagating X-ray

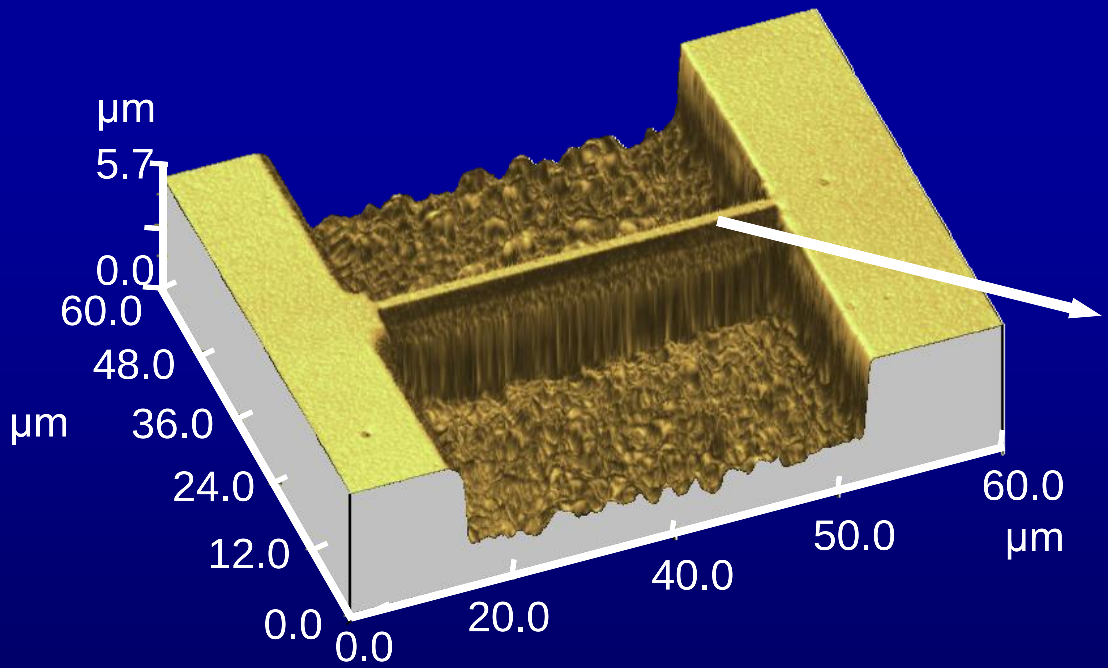
X-ray detector

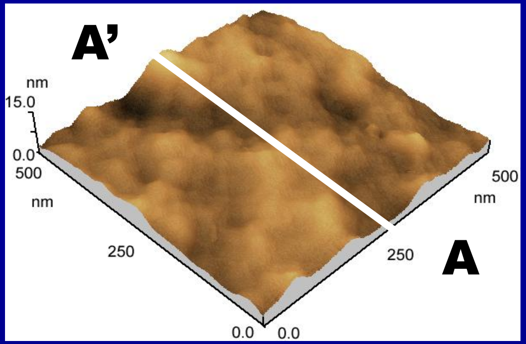
Scanner is acting as a phase object



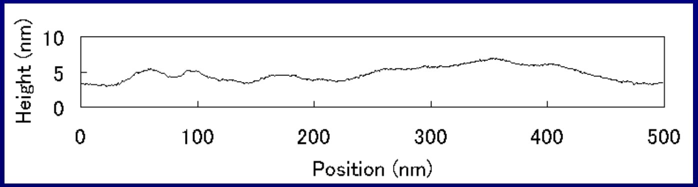
Modified wavefront

Phase is shifted with λ/2.





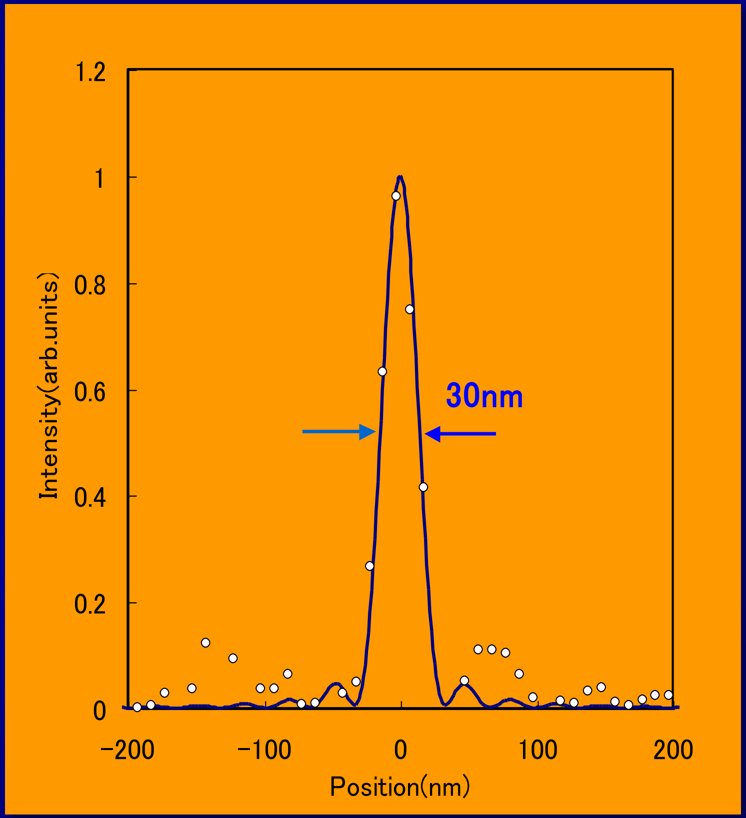
Microroughness at the bridge



A-A' profile

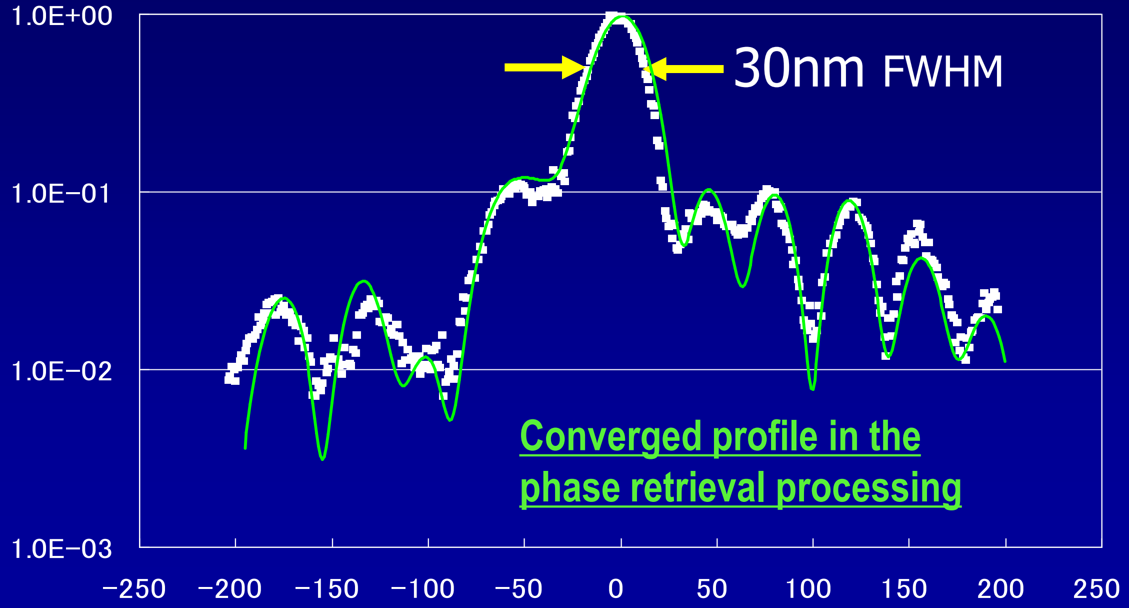
30nm-focusing mirror was employed

for a demonstration of the proposed at-wavelength measurement

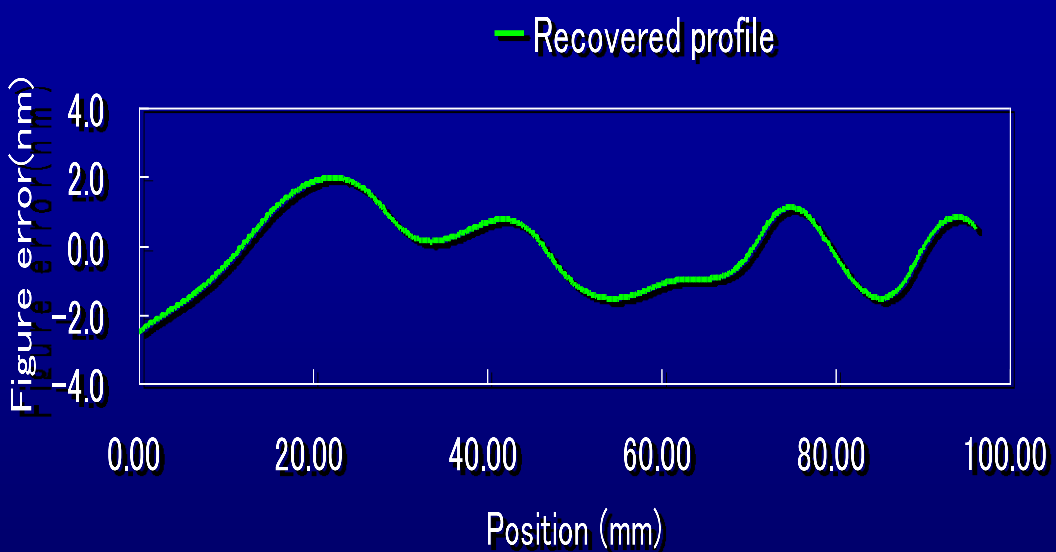


- Not a multilayer optic.
- Surface is coated by Pt.

Performance of phase retrieval

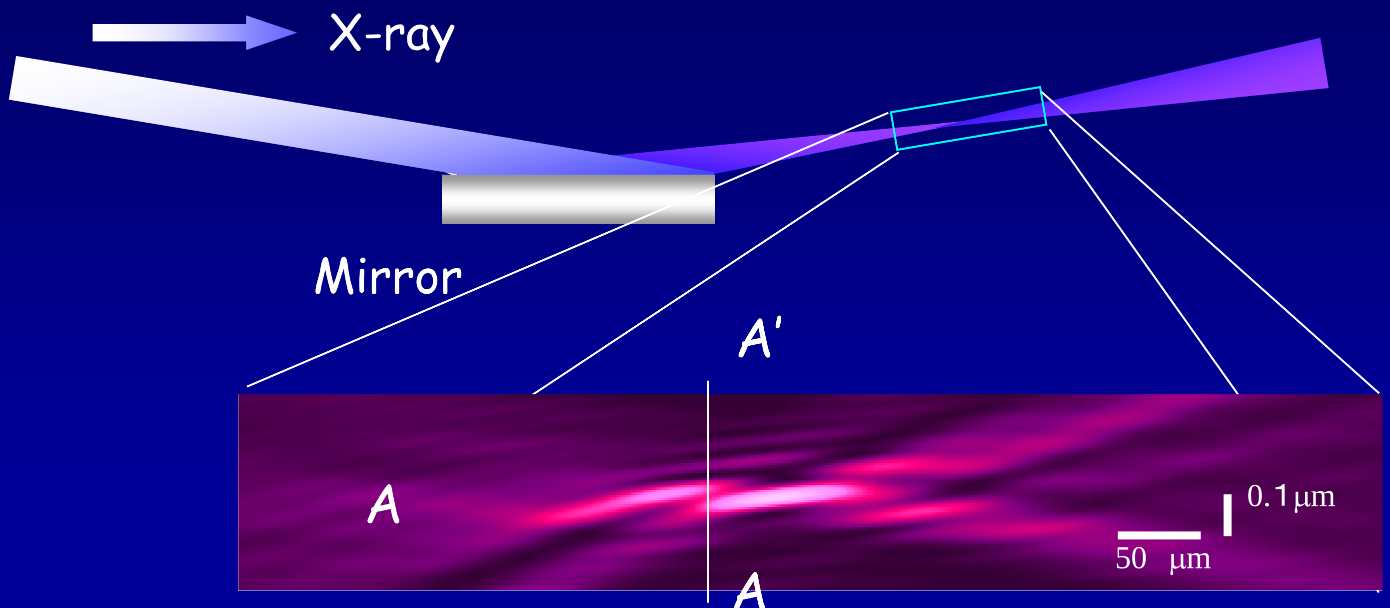


Measured beam profile

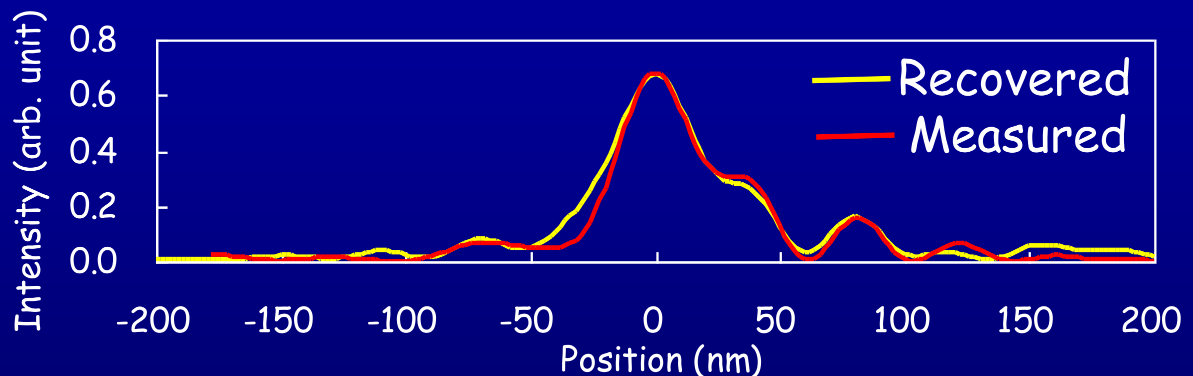


Mimura et al.
Phys. Rev. A (2008)

Recovered wavefield is local-minimum solution or not



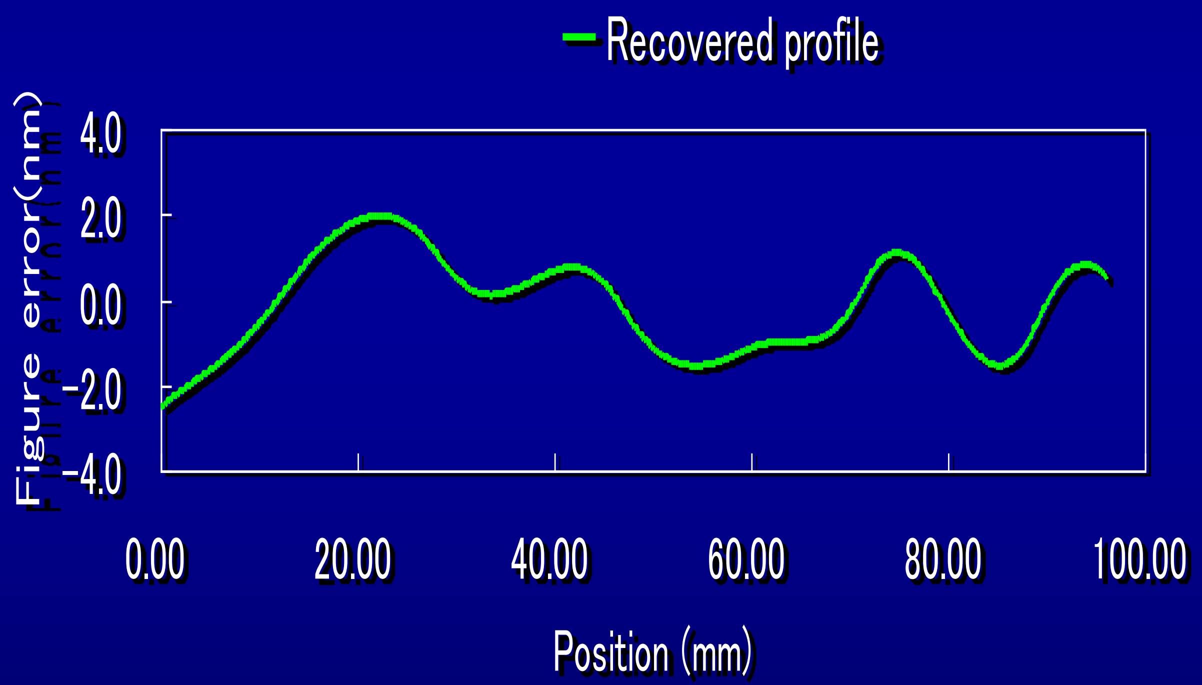
Intensity distribution at beamwaist



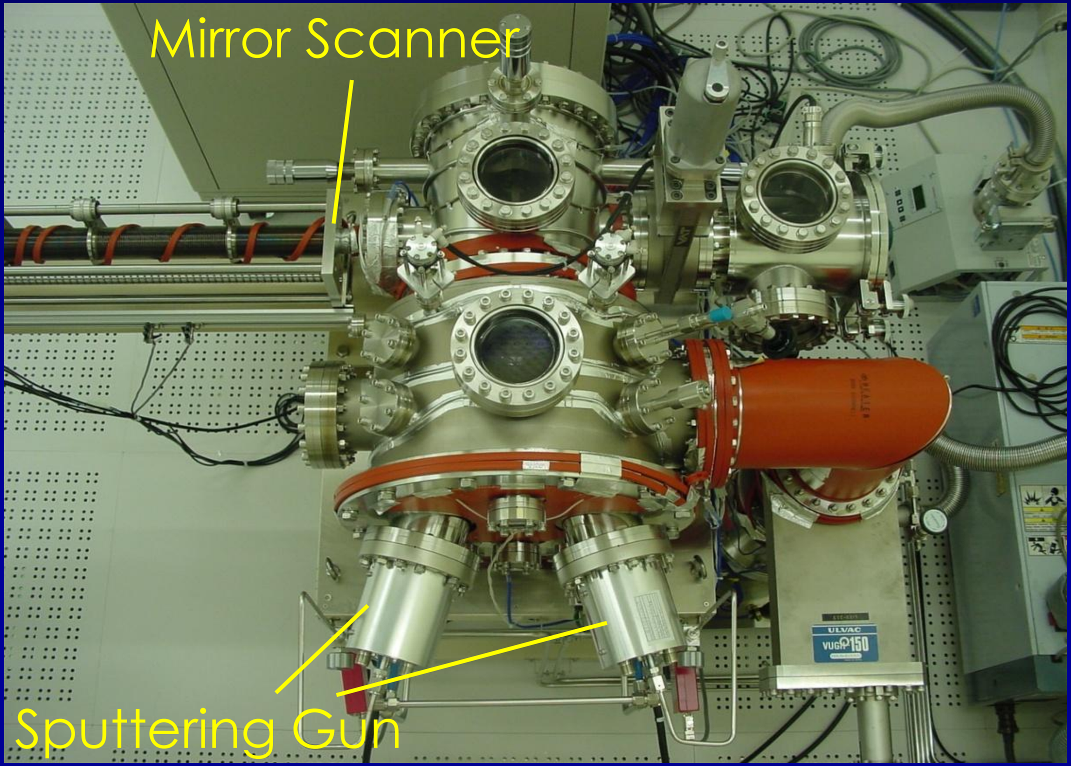
Calculated and measured intensity profiles on A-A' line.
(50μm upstream from the focal point)

Verification

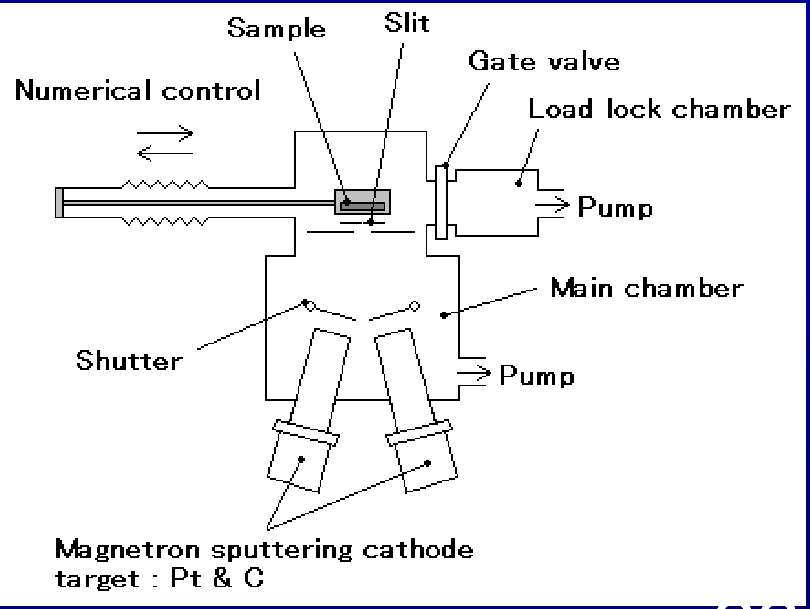
To verify the reliability of the recovered phase error profile, we actually refigured the mirror by differential deposition method (G. Ice) using the recovered profile.



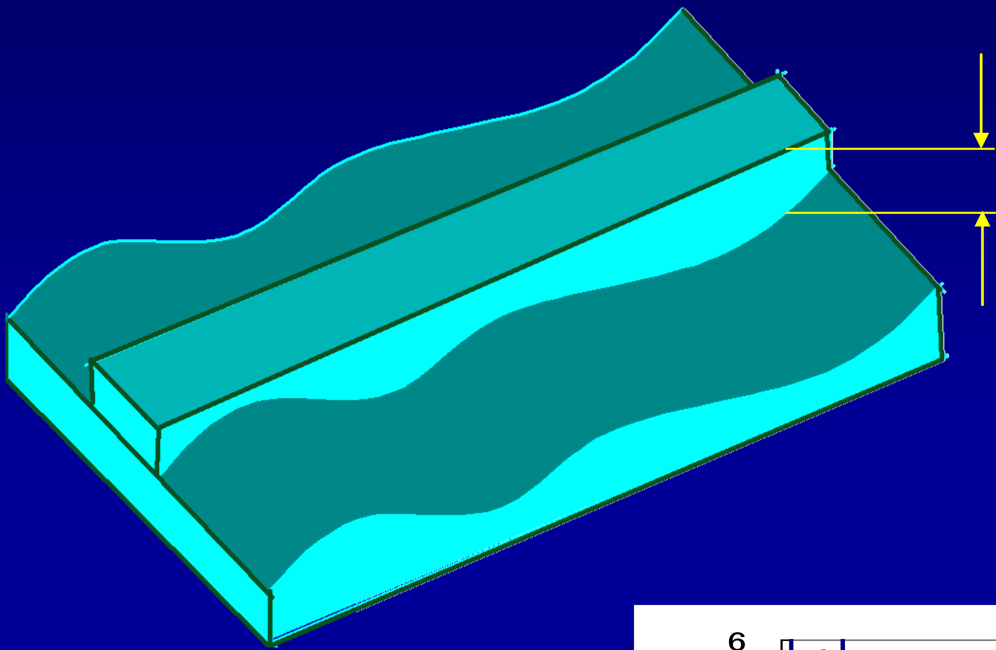
Computer-controlled deposition system

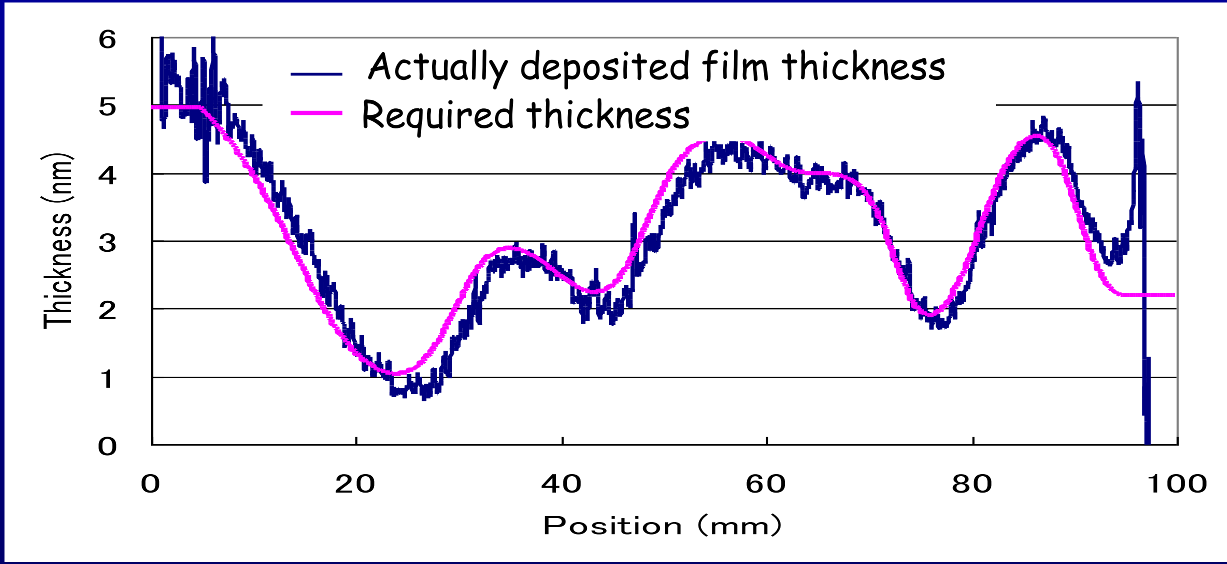


Mirror is placed on the computer-controlled stage, and local deposition can be done through the slit.



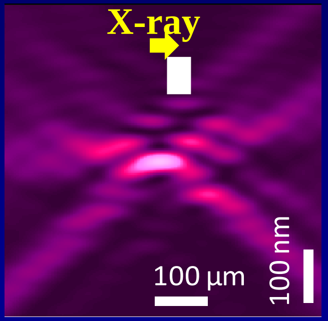
Figuring by differential deposition



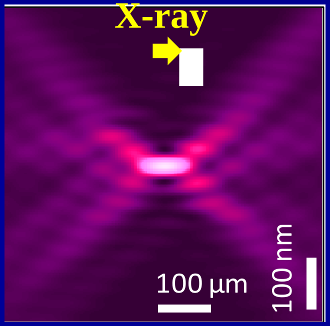


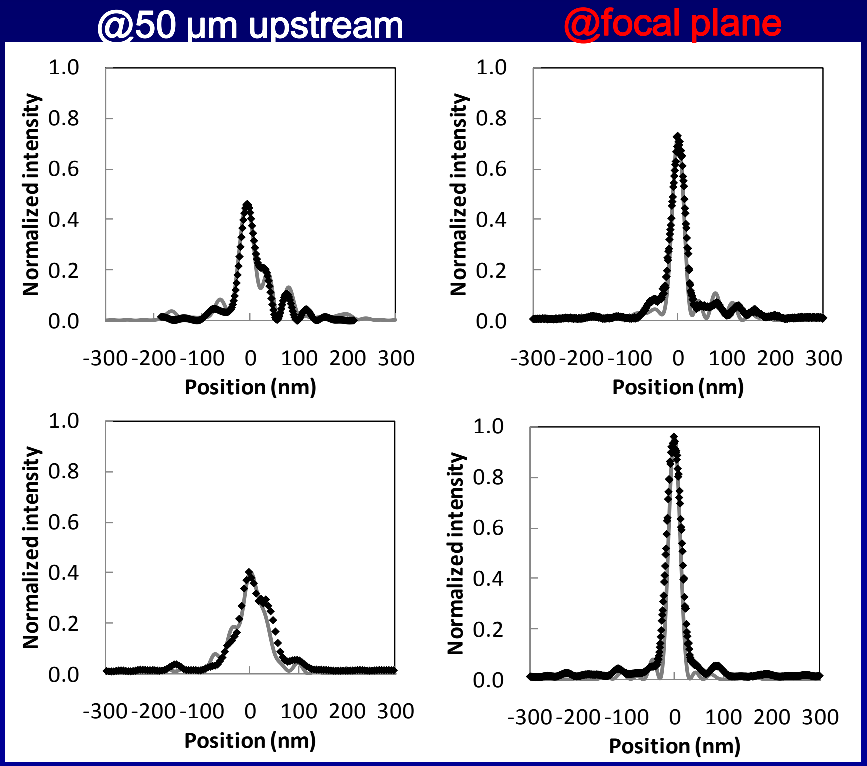
Focused beam profiles before and after DD

Before DD

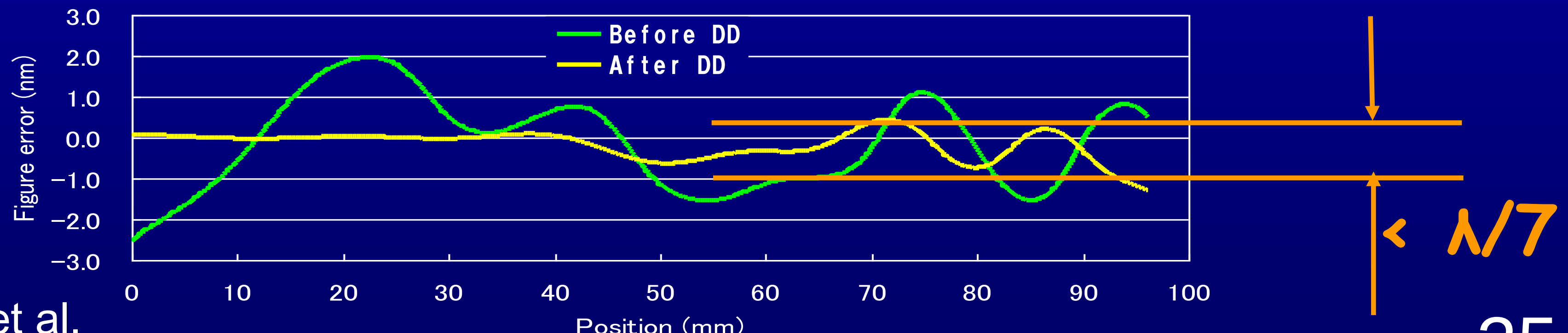


After DD



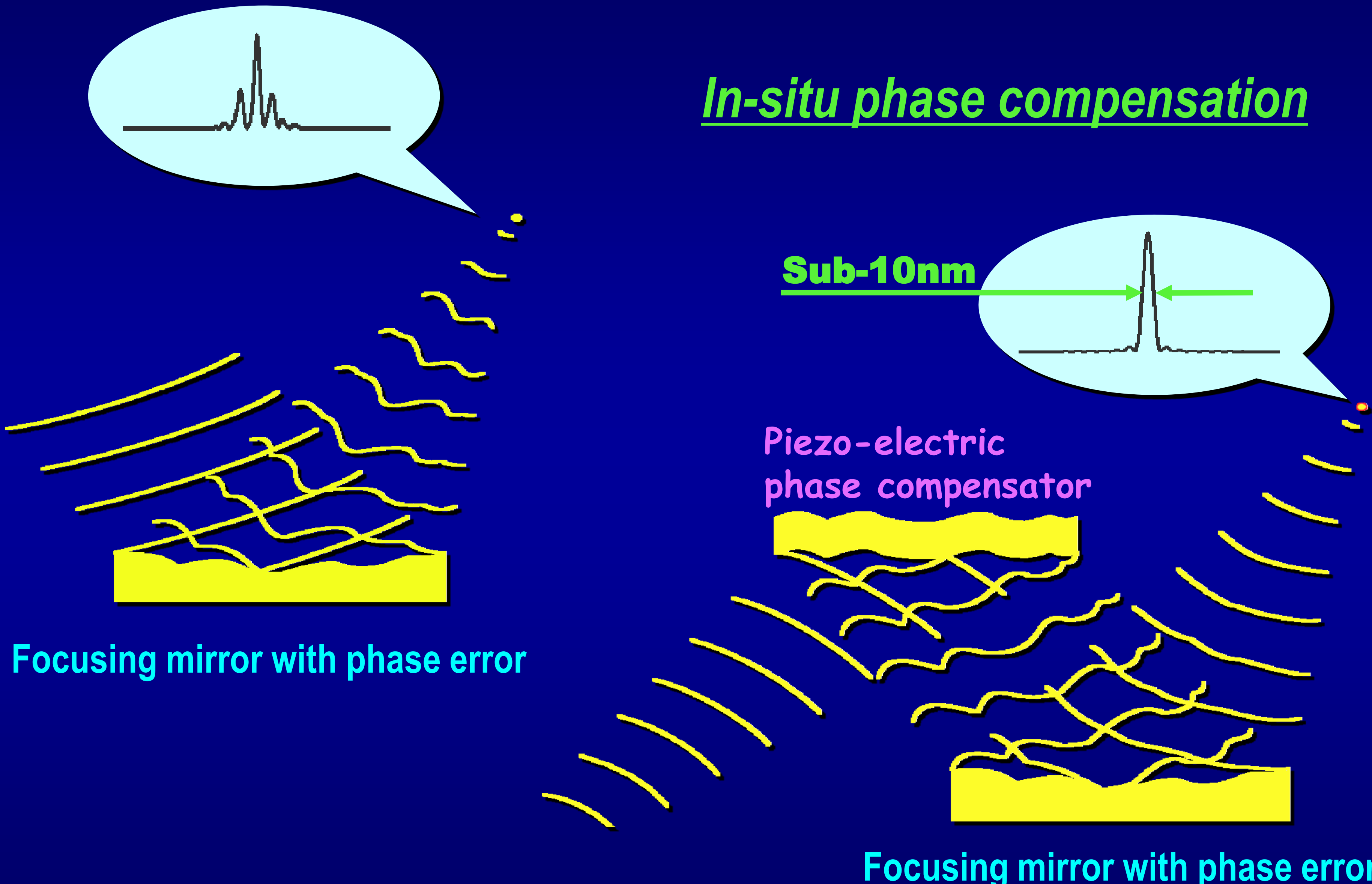


Comparison between the wave fields before and after phase compensation

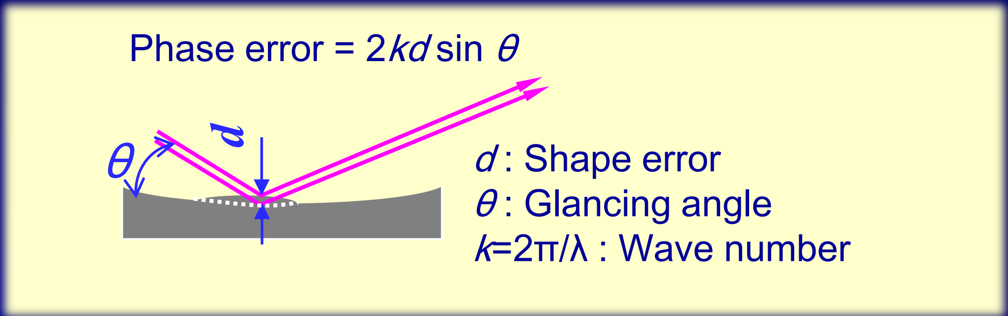


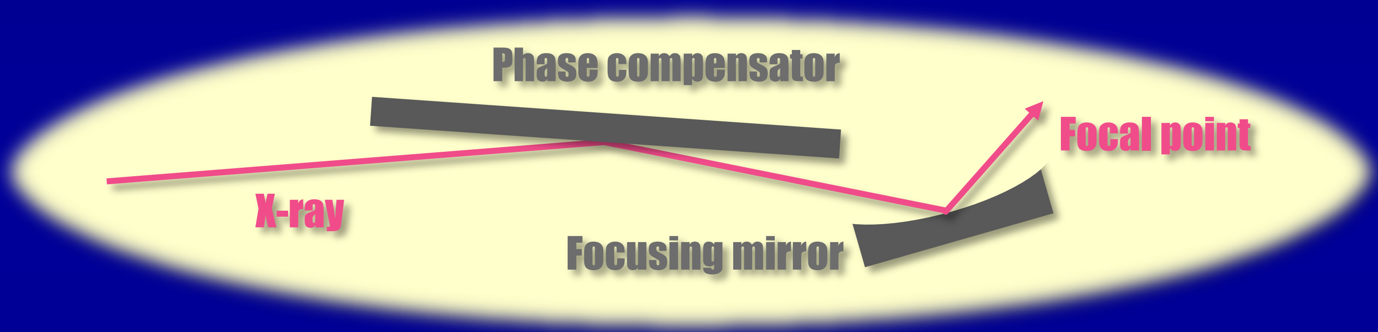
Handa et al. SIA(2008)

On-line compensation of wavefront



Design concept

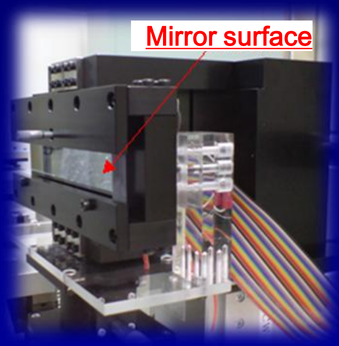


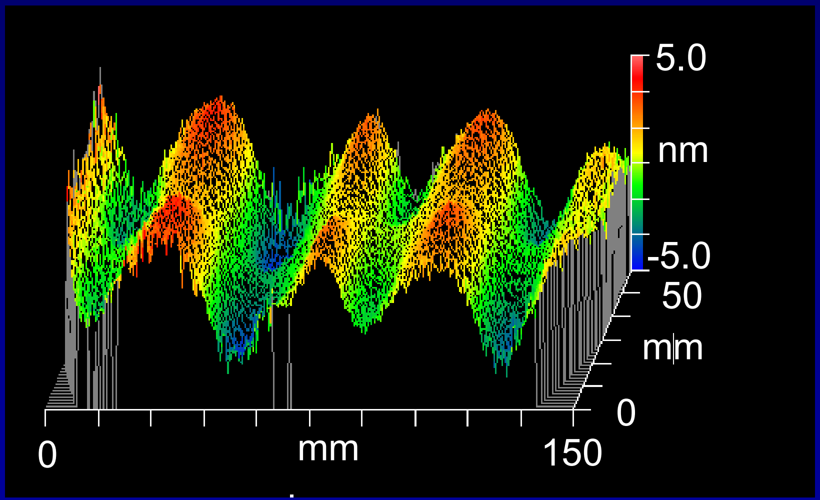


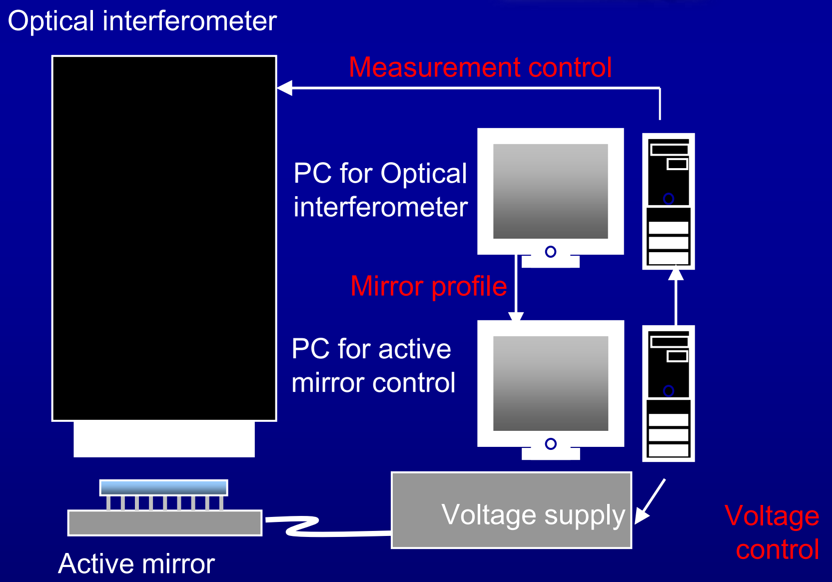
★ **Glancing angle of compensator mirror is N times smaller.**
(However, Consequently the length of the compensator becomes longer)

Required figure accuracy of the compensator mirror becomes N times lower.

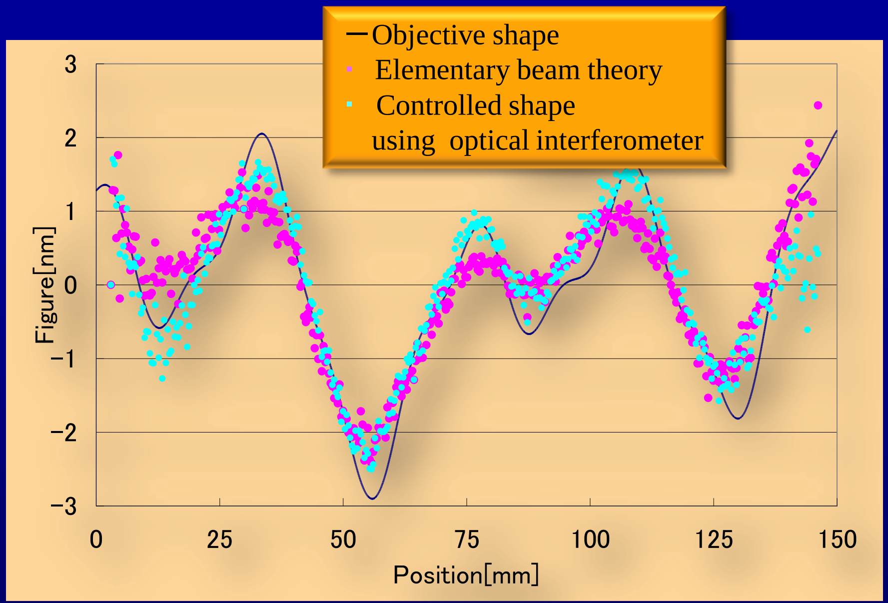
Phase compensator





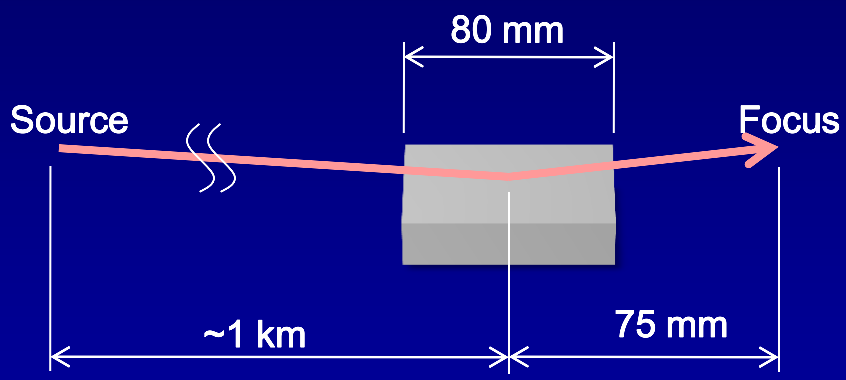


Feedback system



Kimura et al.,
SPIE O&P (2008), Jpn. J. Appl. Phys (2009)

Sub-10nm focusing mirror



X-ray energy	20 keV
Mirror length	80 mm
Focal distance	75 mm
Glancing angle	7.0 mrad
Multilayer material	$[Pt/C]_{20}$
Substrate material	quartz glass

$$\Lambda = \frac{\lambda}{2\sqrt{n^2 - \cos^2\theta}}$$

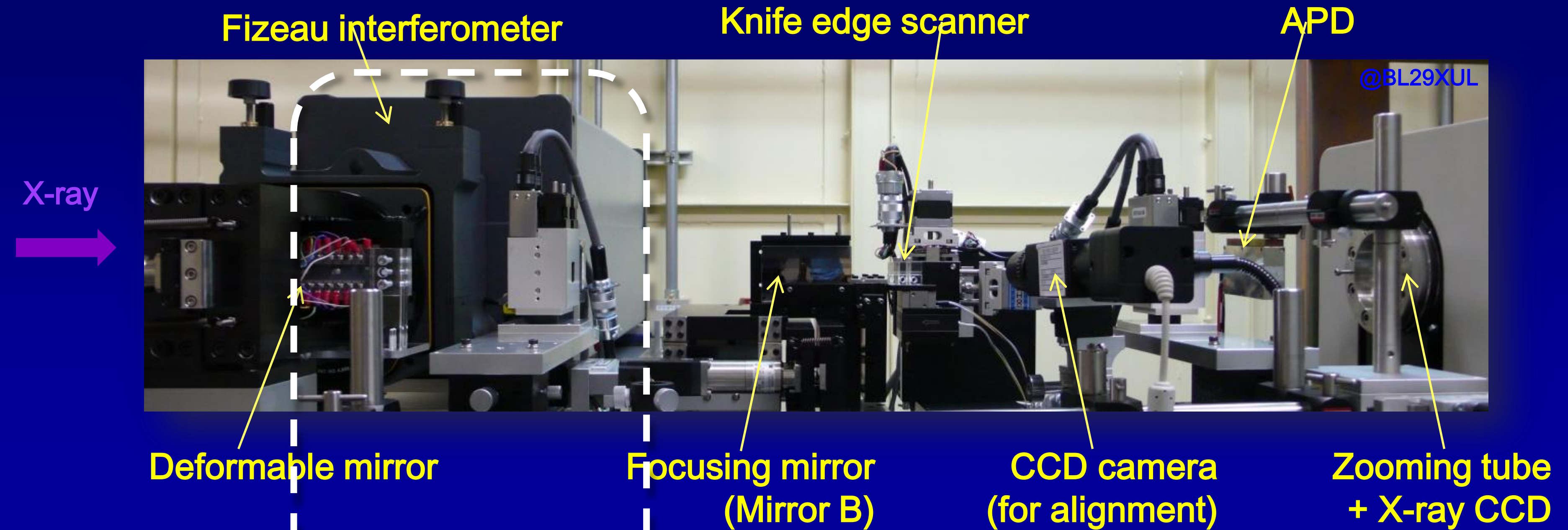
Λ : d-space
λ : X-ray wavelength
n : Index
θ : Glancing angle

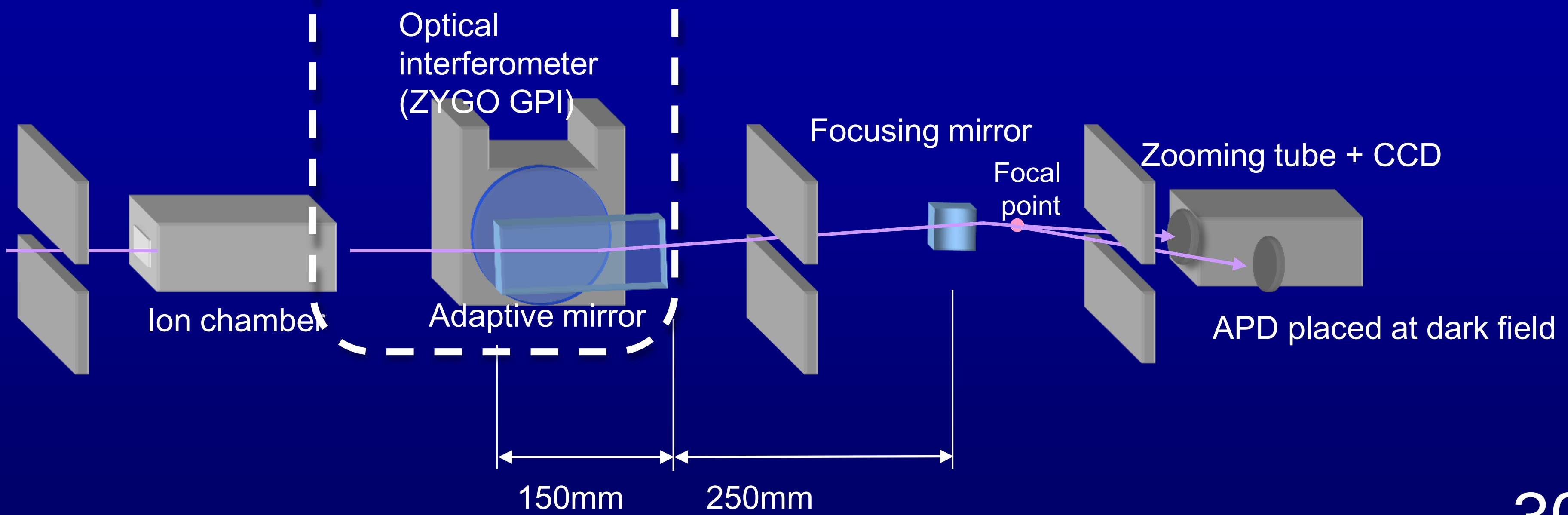
EEM Machine

Micro- and RAD- Stitching Optical Interferometry

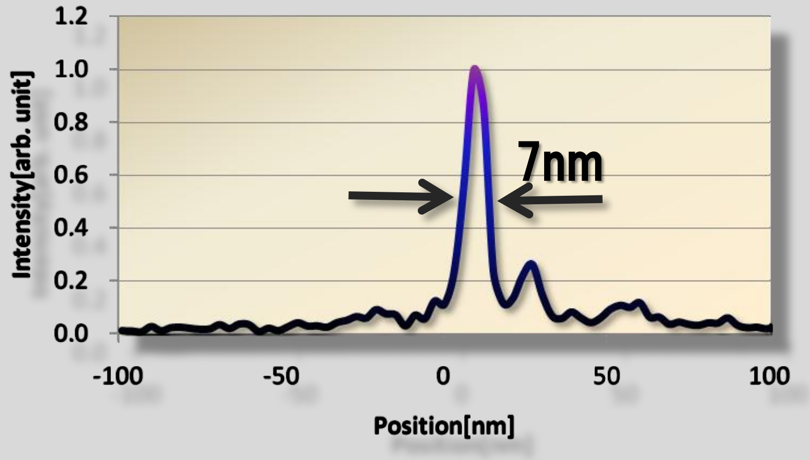
Laterally-Graded Multilayer Coater

Optical configuration for active phase compensation

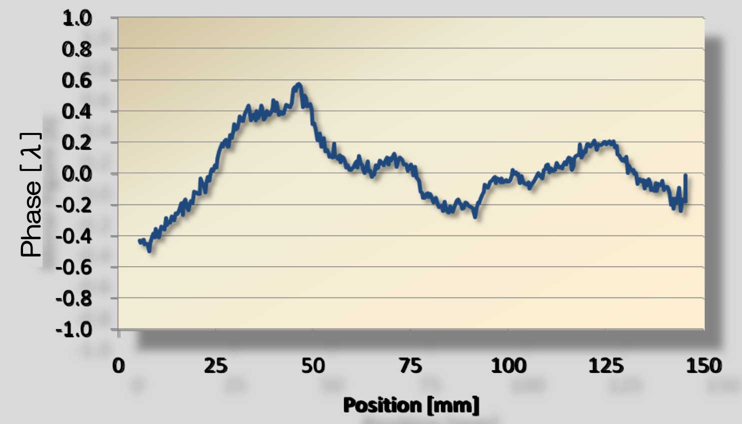




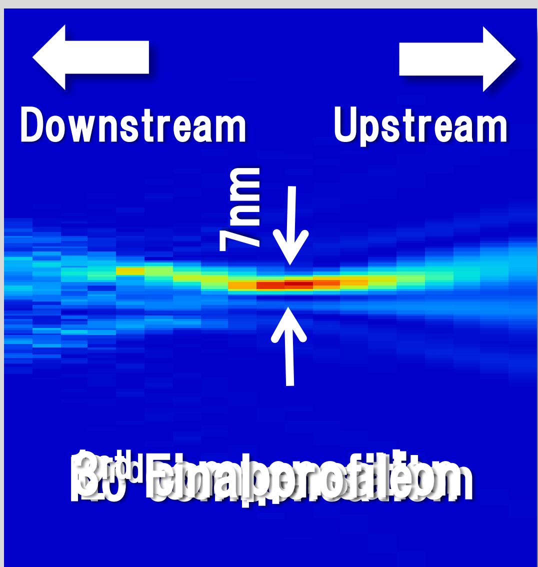
Sub-10nm focusing by using phase compensator



Profile at focal point



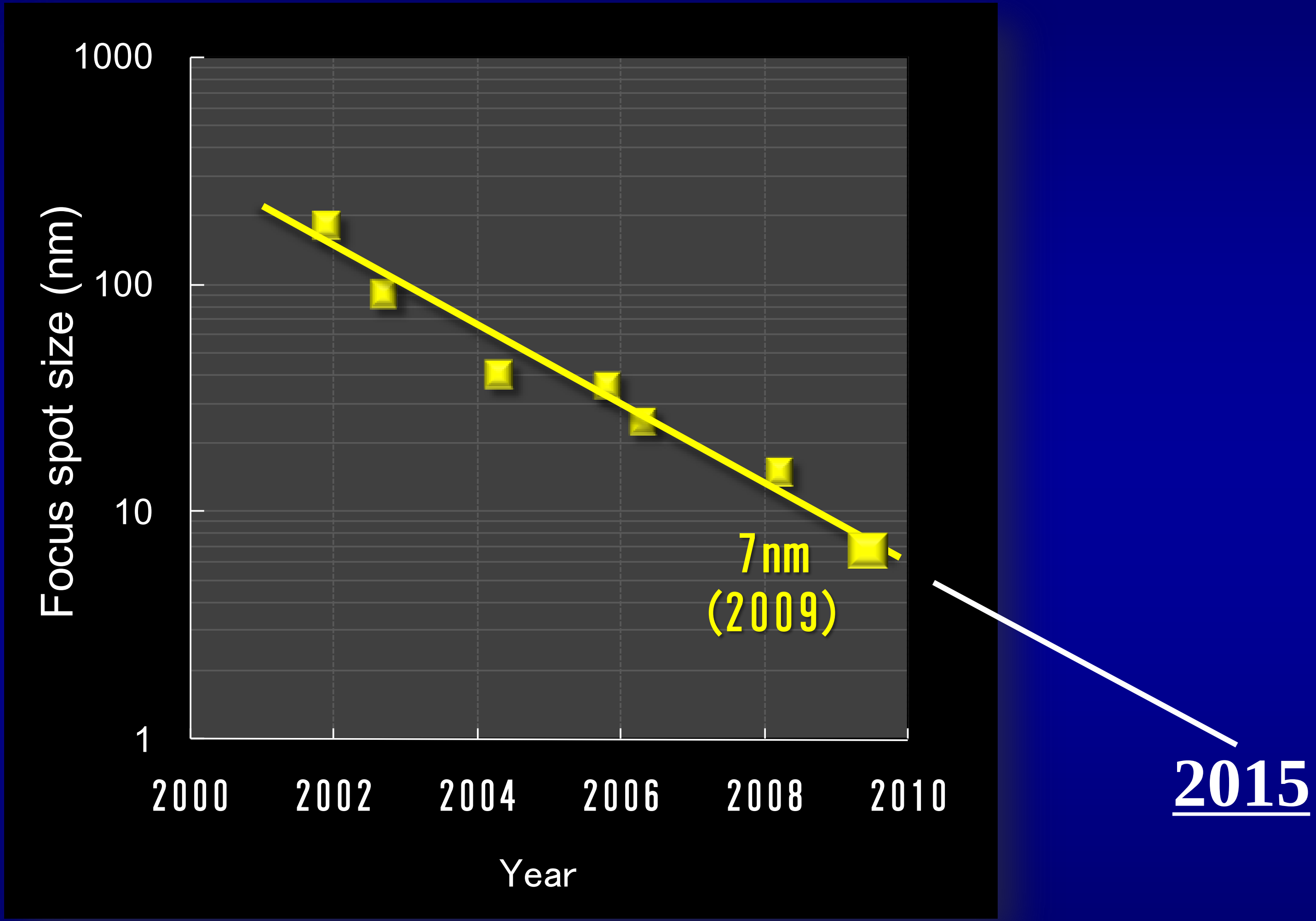
Compensated phase profile
(shape of compensation mirror)



Maximum phase compensated here was λ/2.
λ was 0.06 nm.

Beam waist structure

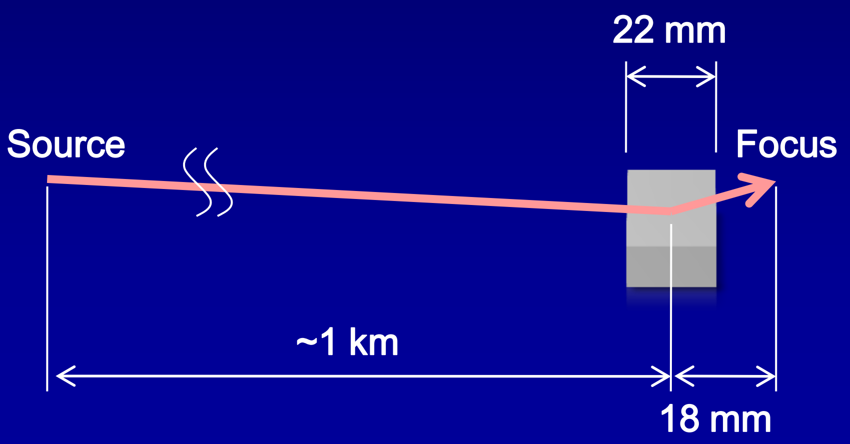
Nature Phys. (2010)



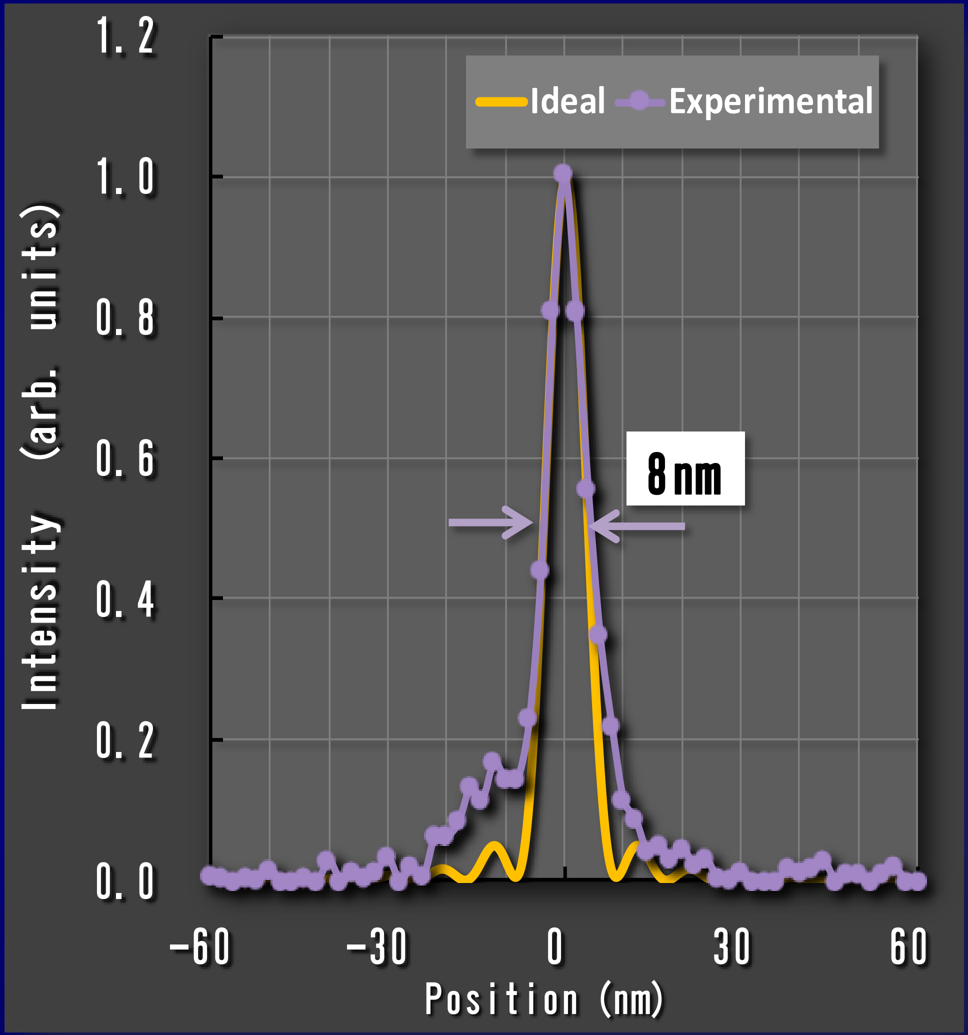
IC

This is the smallest light beam human-made.

Another mirror



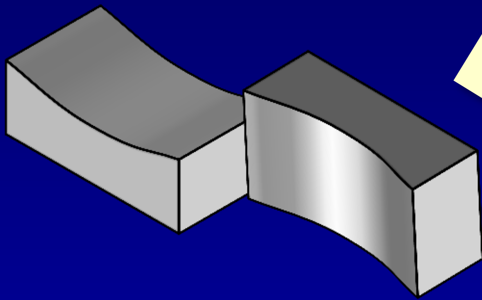
X-ray energy : 20 keV
Mirror length : 22 mm
Focal distance : 18 mm
Glancing angle : 7.0 mrad
Multilayer material : $[Pt/C]_{20}$
Substrate material : quartz glass

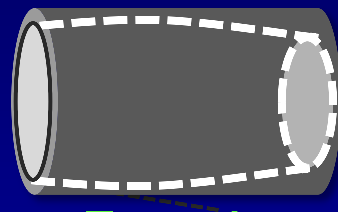


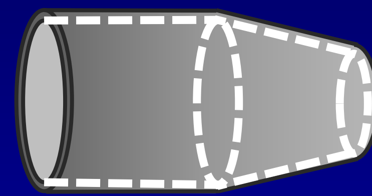
Achromatic imaging device (AKB Mirrors)

Total reflection axial-symmetric optics

KB mirrors







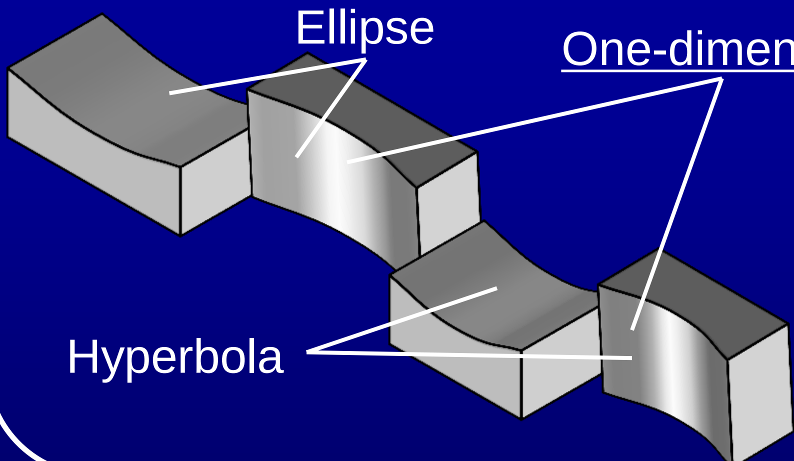
Wolter mirror

easy to fabricate

It fills Abbe's sine condition

Advanced Kirkpatrick–Baez mirrors

R. Kodama et al., *Optics Letters* **21** (17), 1321-1323 (1996).



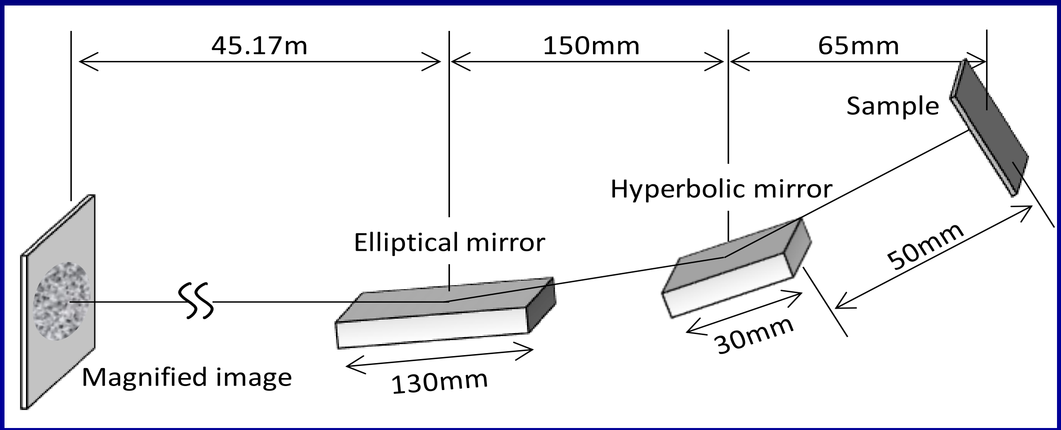
☆Advantage

- Wide field of view
- Easy fabrication

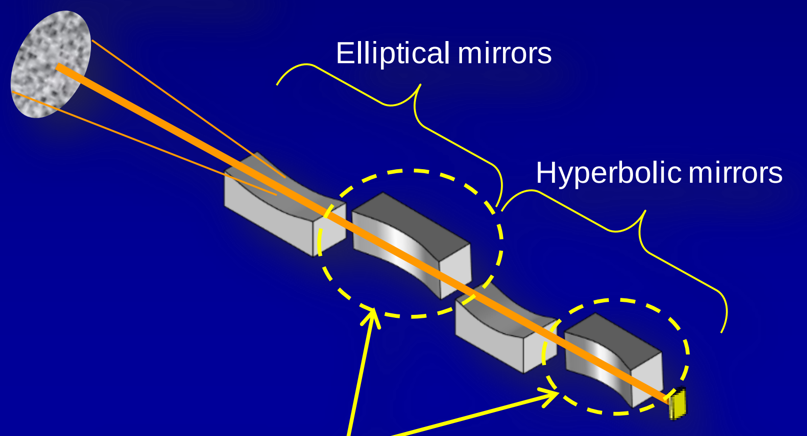
We tried to realize AKB mirrors having diffraction-limited performance.

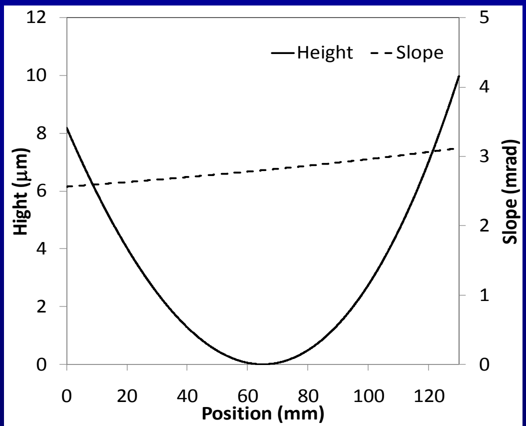
1-dimentional Wolter mirror system

Magnification: 385x , Size of the point spread function: 43nm

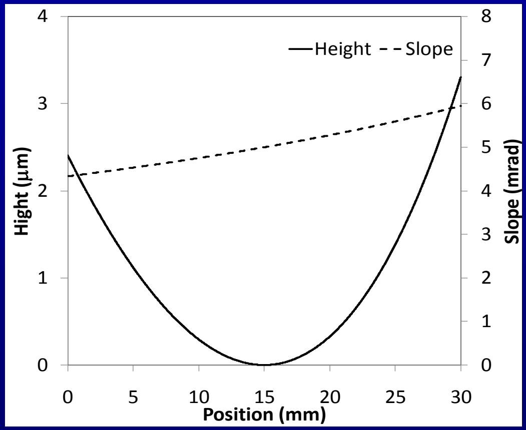


Optical system of a one-dimensional Wolter optics



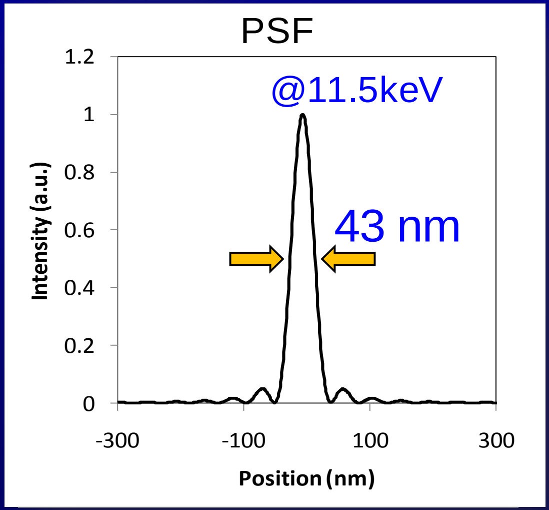


Elliptical mirror



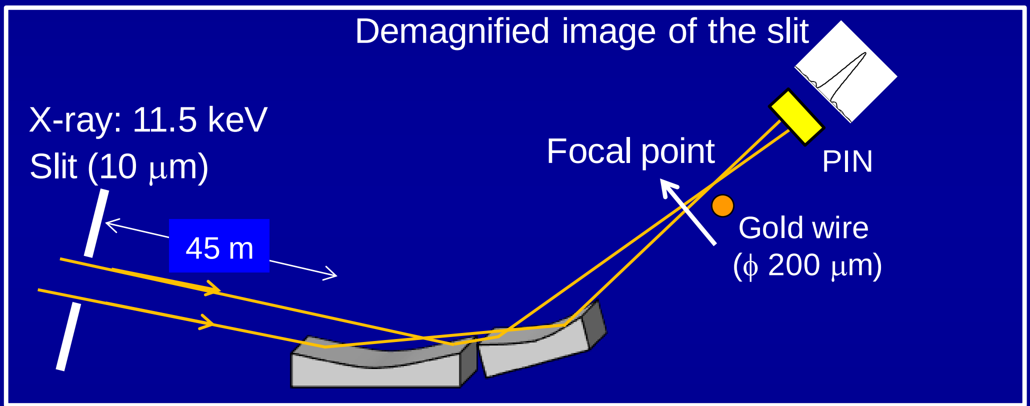
Hyperbolic mirror

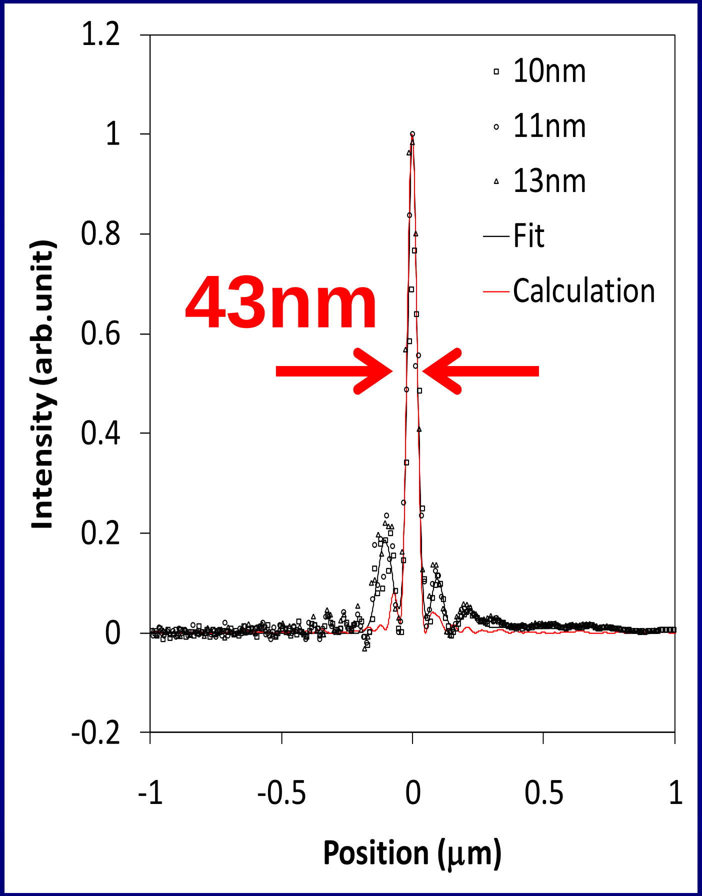
Mirror figures



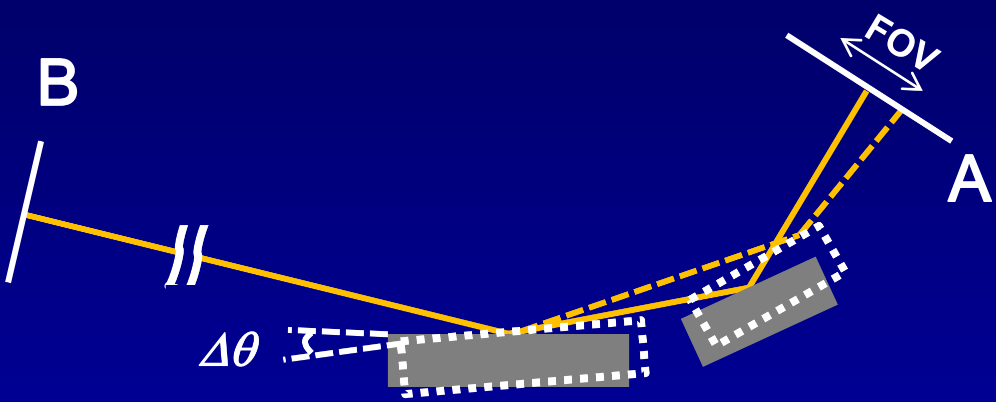
Spatial resolution test

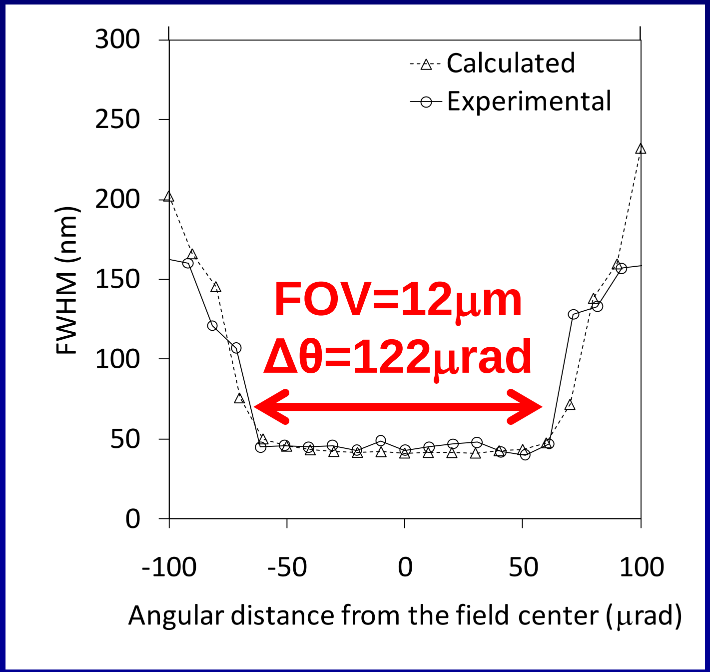
Demagnifed imaging system





Evaluation of FOV



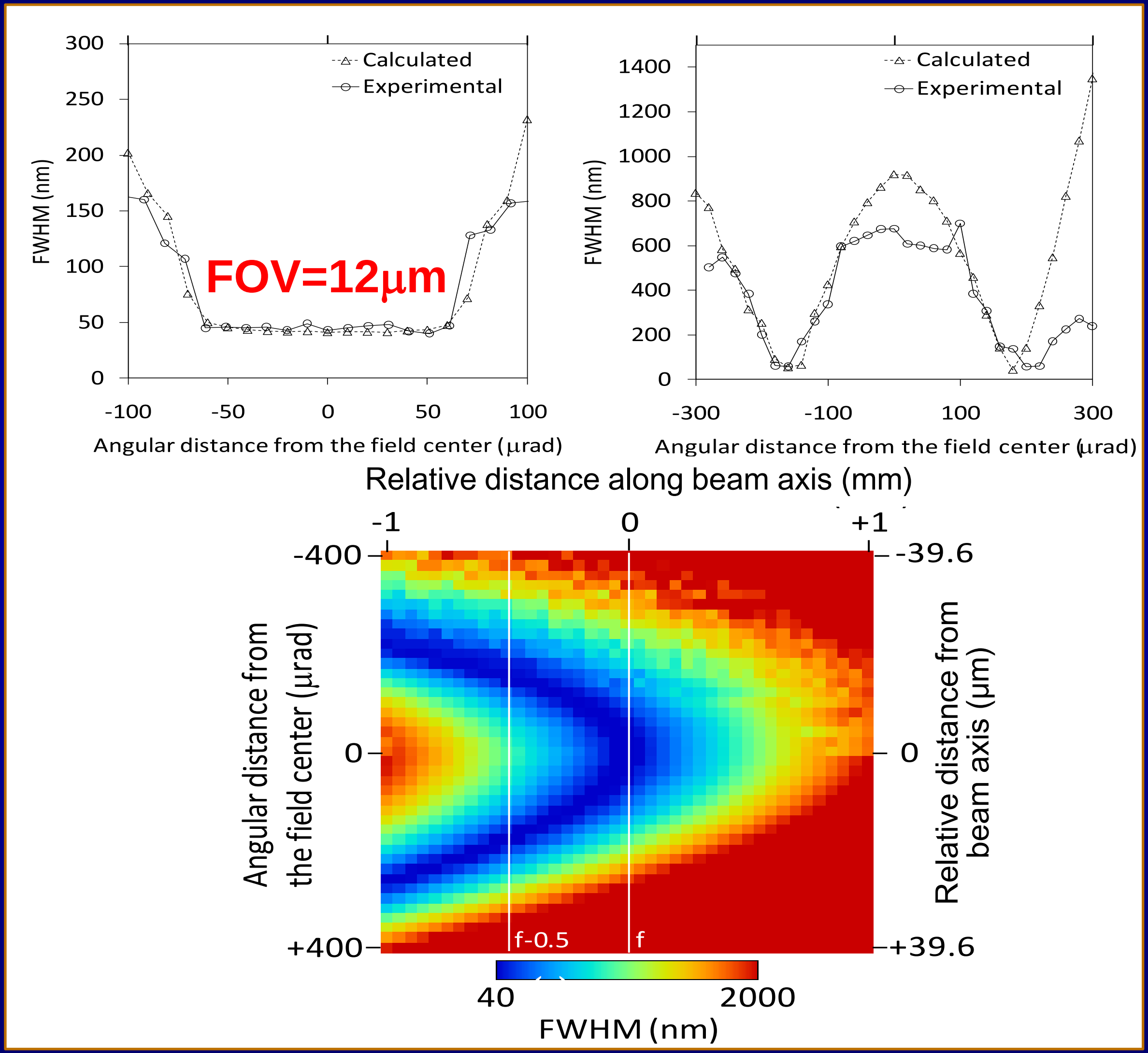


- To evaluate a field of view (FOV), we measured beam size on plane A by changing the glancing angle (Δθ).
- This procedure is equivalent to shifting relevant points on the planes A and B.

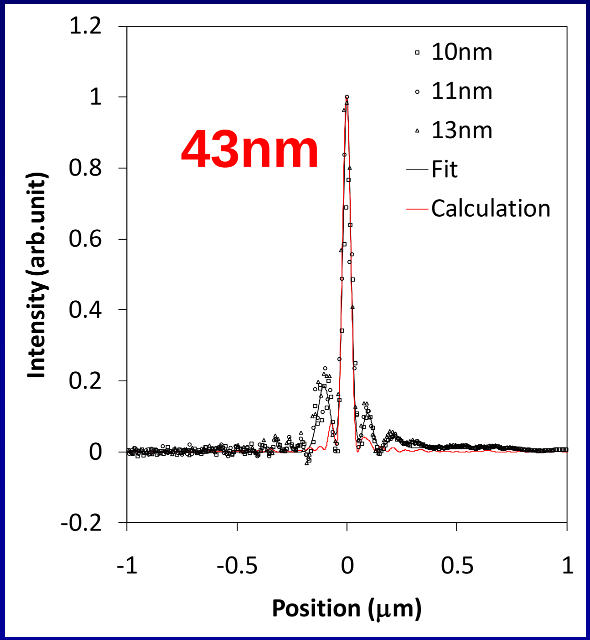
◆Very wide angular width (Δθ) of 122 μrad was obtained.

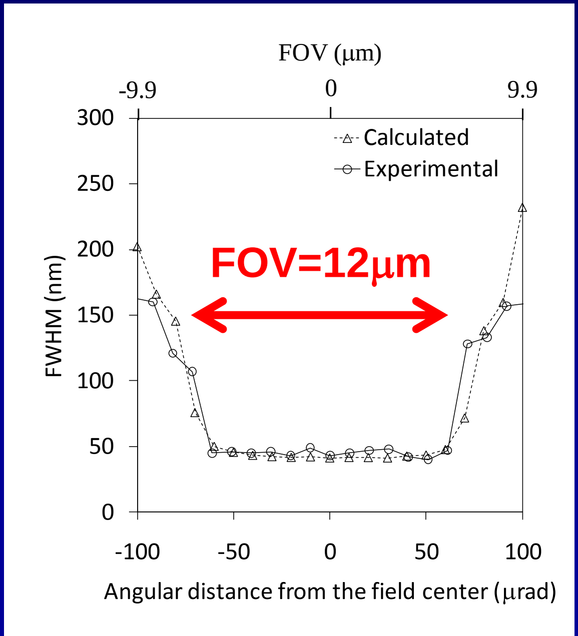
◆It is equivalent to the FOV of 12μm.

Field curvature aberration



Summary of AKB development



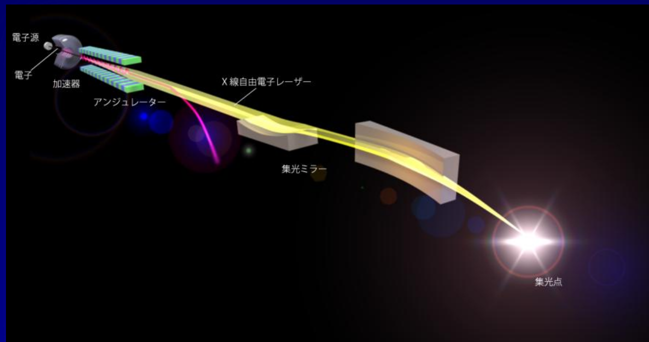


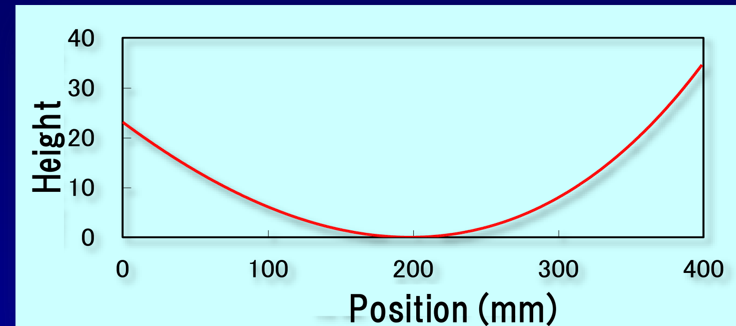
1-dimensional Wolter mirror demonstrated theoretically expected performances both in the resolution and FOV!

Matsuyama et al., Optics Lett (2010)

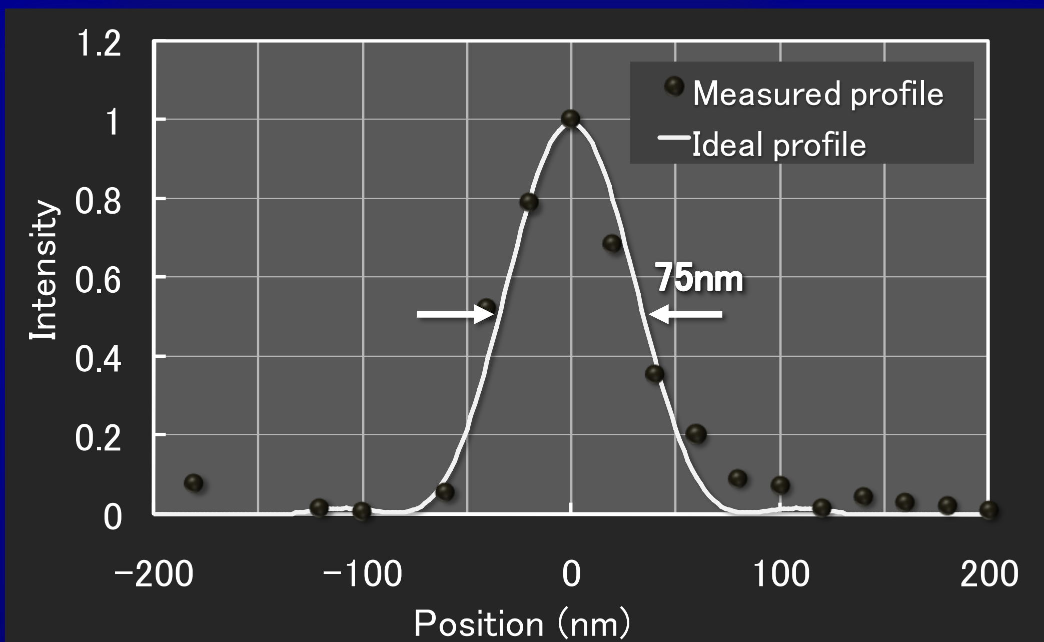
AKB optics will be useful in coming XFEL experiment.

XFEL focusing





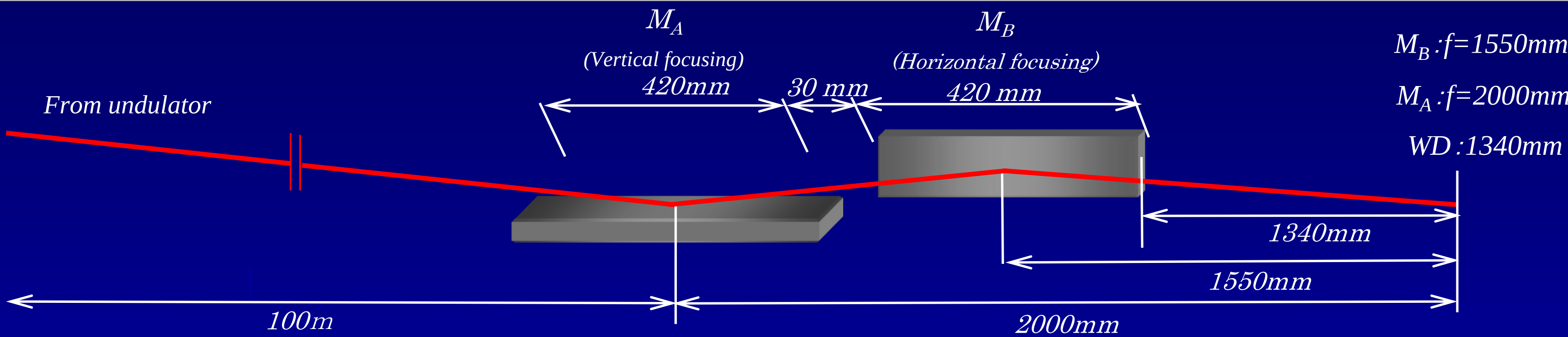
WD: 350mm

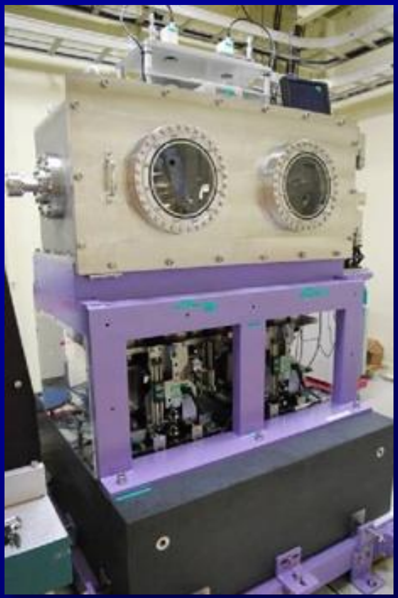


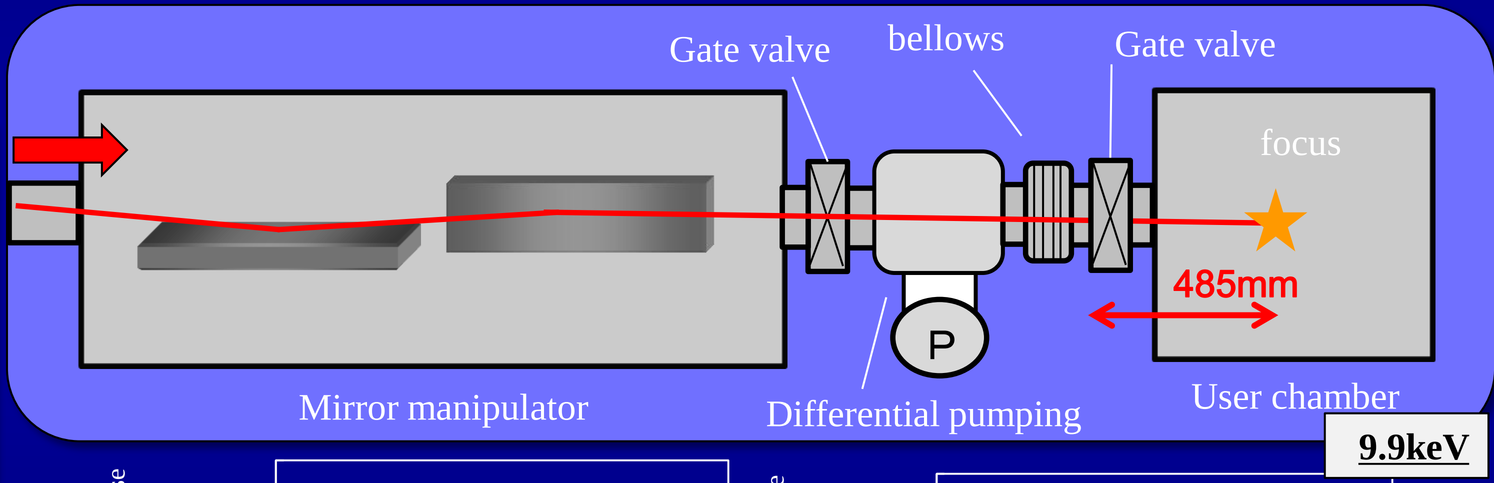
We have already developed 1μm-level focusing unit for day-1 system of Japanese XFEL, and also fabricated and tested sub-100nm focusing mirror.

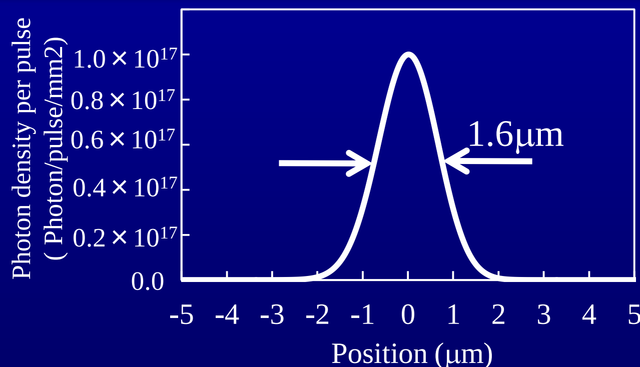
We are now trying to realize 2-dimensional sub-50nm focusing of XFEL.

1μm-level focusing

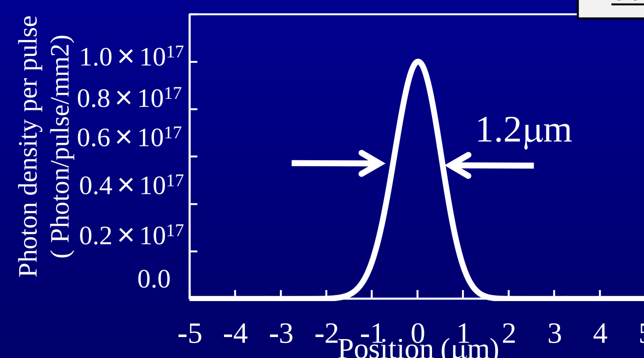






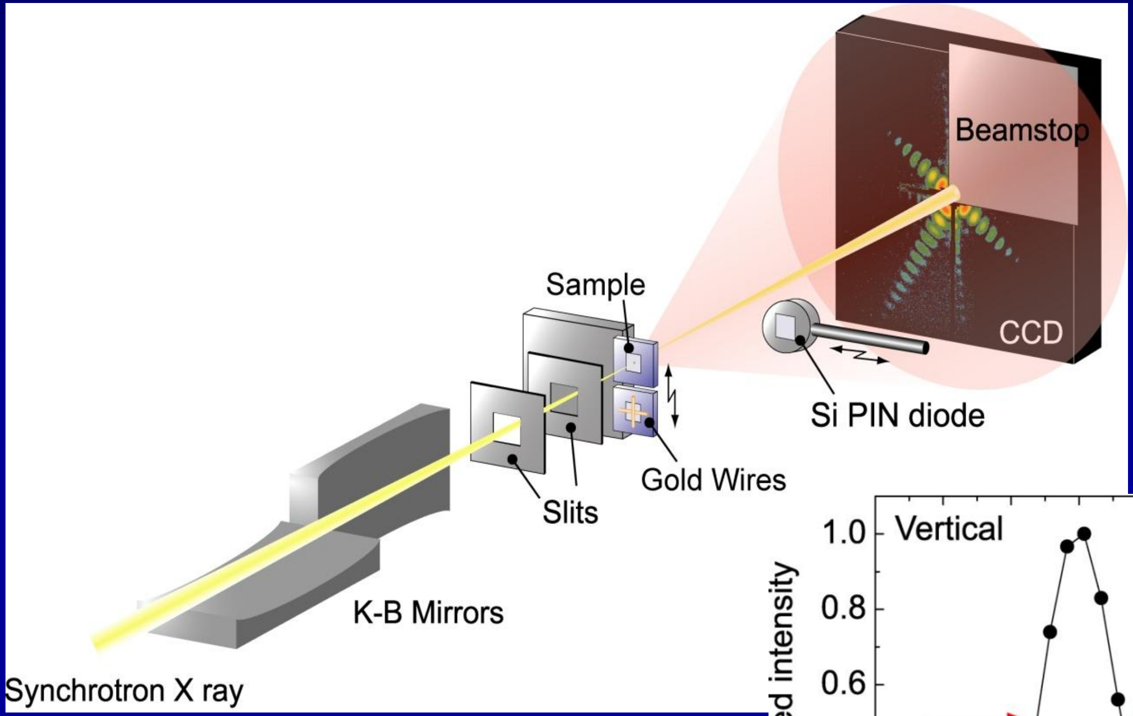


Vertical direction



Horizontal direction

Focused x-ray illumination for diffraction microscopy

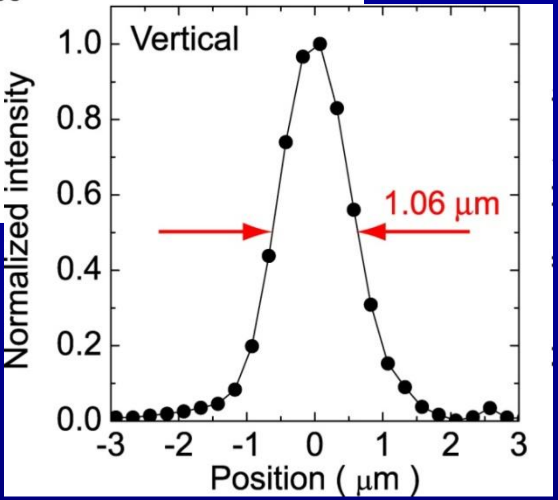


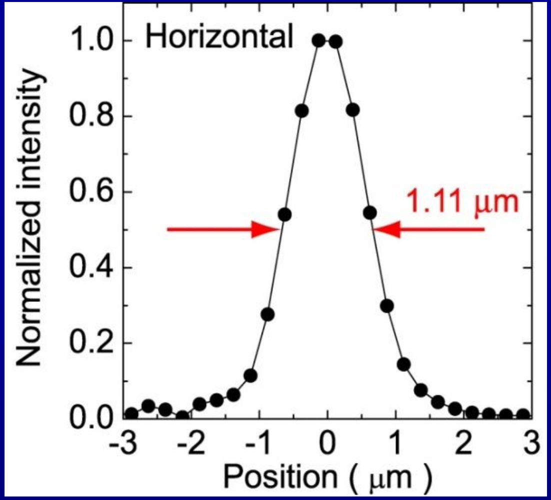
@SPring-8 BL29XUL

How wide area in k-space can we observe?

We must heighten the photon density at sample.

Beam profiles

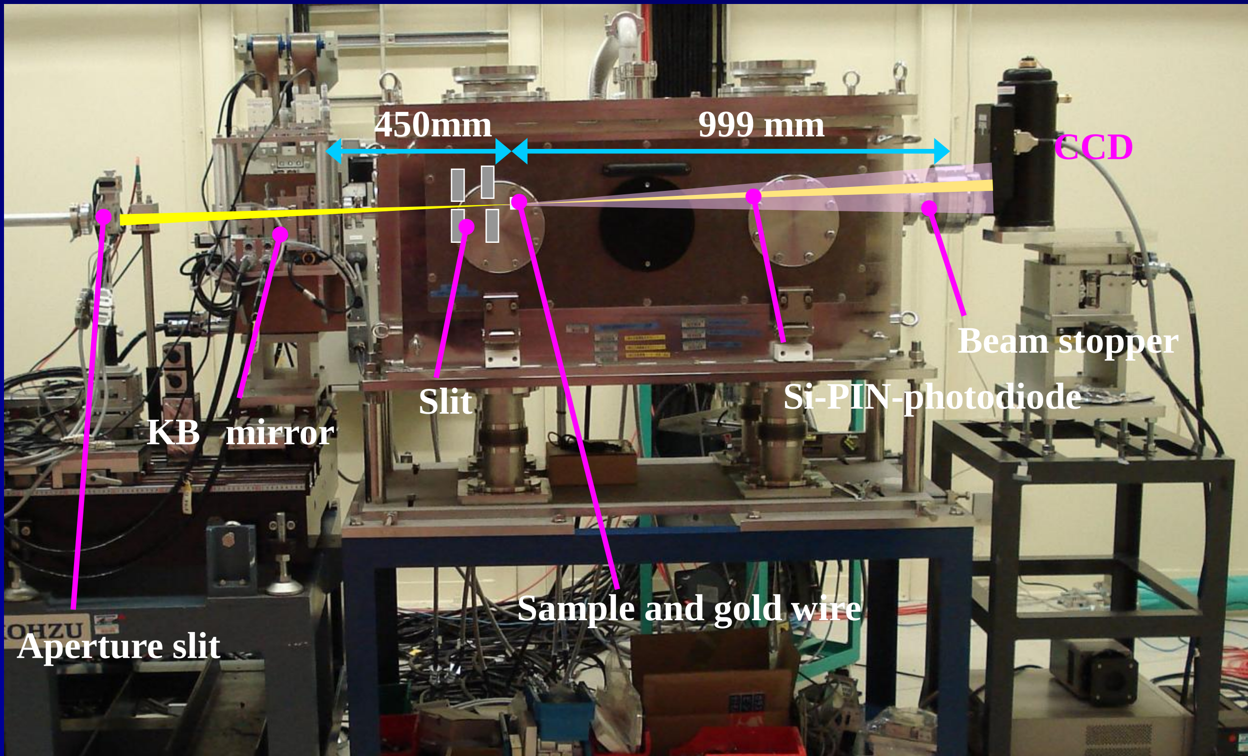




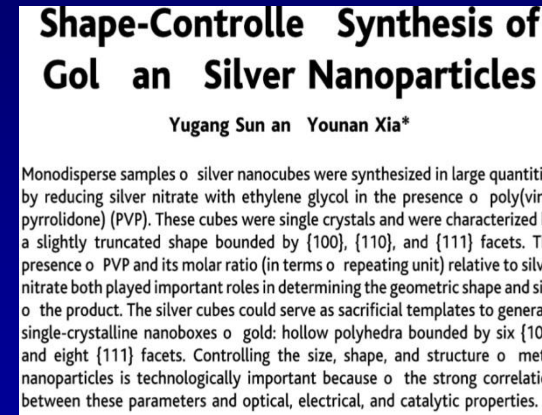
- Spot size: ~ 1 μm
- Photon density: ~ 1.0×10^4 photons/nm^2/s

➡ More than 100 times larger

Set-up and samples



Science 298, 2176 (2002)

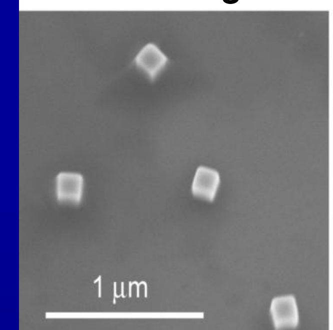


Shape-Controlle Synthesis of Gol an Silver Nanoparticles

Yugang Sun an Younan Xia*

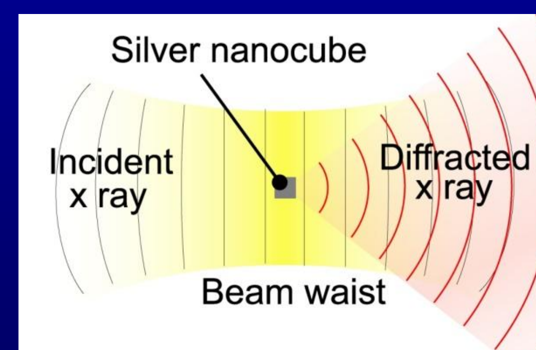
Monodisperse samples o silver nanocubes were synthesized in large quantities by reducing silver nitrate with ethylene glycol in the presence o poly(vinyl pyrrolidone) (PVP). These cubes were single crystals and were characterized by a slightly truncated shape bounded by {100}, {110}, and {111} facets. The presence o PVP and its molar ratio (in terms o repeating unit) relative to silver nitrate both played important roles in determining the geometric shape and size o the product. The silver cubes could serve as sacrificial templates to generate single-crystalline nanoboxes o gold: hollow polyhedra bounded by six {100} and eight {111} facets. Controlling the size, shape, and structure o metal nanoparticles is technologically important because o the strong correlation between these parameters and optical, electrical, and catalytic properties.

SEM image



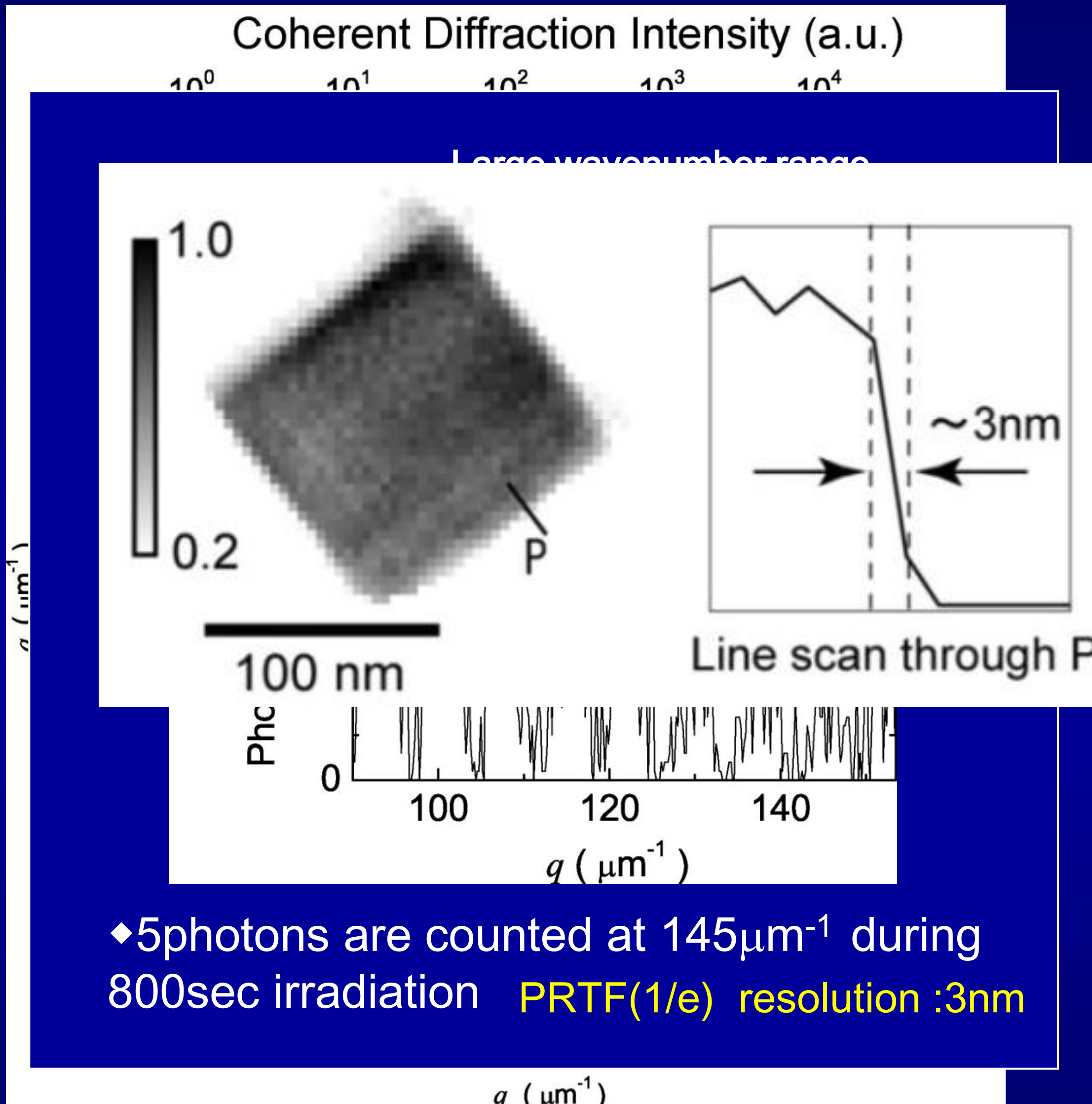
Ag nanocube

～100 nm

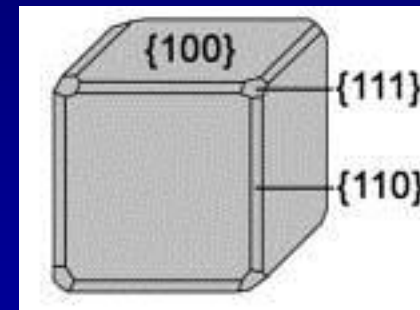


- ◆X-ray energy：12keV
- ◆Working distance：450mm
- ◆Camera length：999mm
- ◆ CCD (Princeton Instruments PI-LCX:1300)

  Pixel size: 20μm
  1300×1340 pixels



◆5photons are counted at 145μm^{-1} during 800sec irradiation PRTF(1/e) resolution :3nm



$$|q| = 2\sin(\Theta/2)/\lambda$$

λ: wavelength

Θ: Scattering angle

Sinc function: $$\frac{\sin(\alpha q)}{\alpha q}$$

Exposure time：800sec, 1.5x10^{11} Photons to the cube

Y.Takahashi et al., Phys. Rev. B 80, 054103 (2009).

Summary

- Achromatic total-reflection mirrors realized sub-30nm focusing of hard X-rays.
- In-site wavefront correction are promising techniques to construct highly accurate optical system of hard X-rays.

- KB mirrors could reach sub-10nm focusing.
- AKB mirrors enable achromatic imaging of incoherent x-rays with sub-50nm-resolution.
- Focused X-ray by KB mirrors could heighten the spatial resolution in diffraction microscopy.

Thank you for your kind attention.